September 30, 2008

Cheiron School 2008

X-ray Beamline Design

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SPring-8/JASRI

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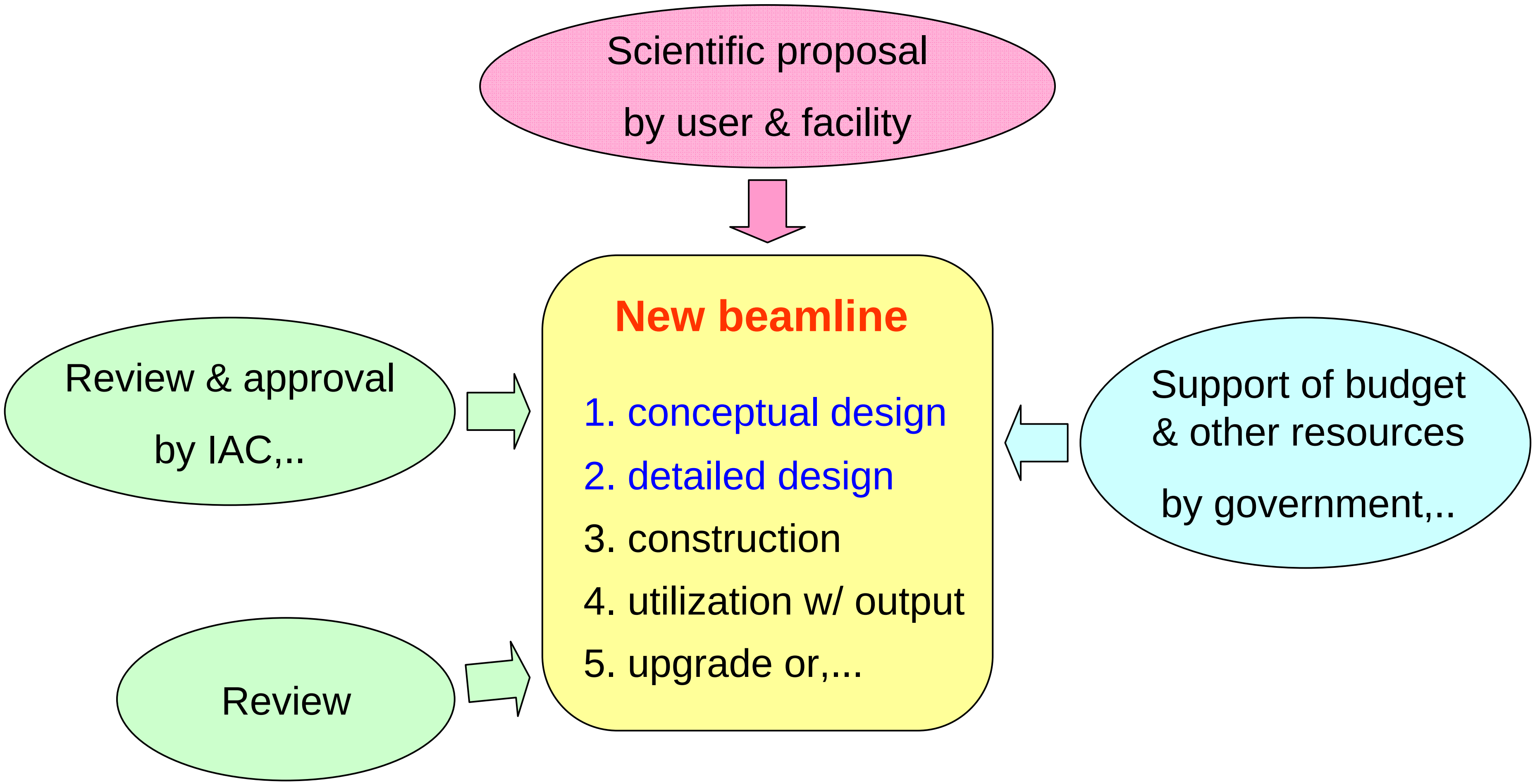
Process of beamline construction

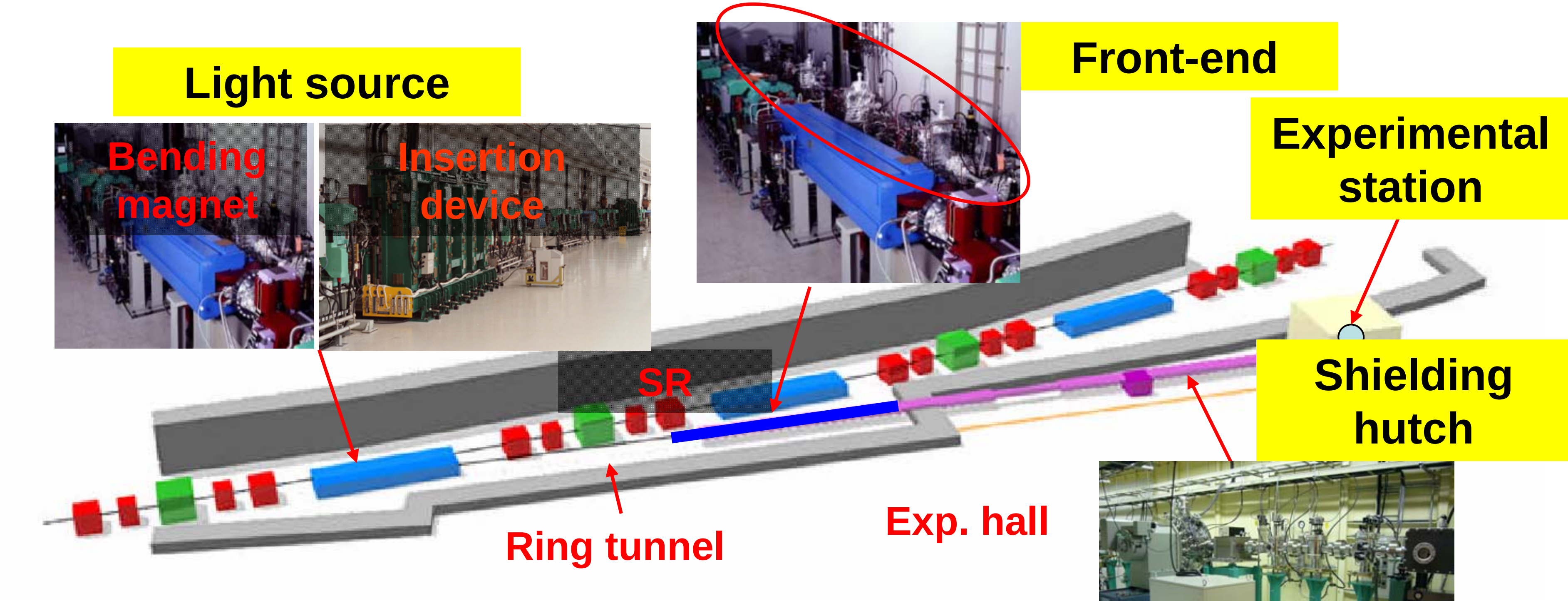


Beamline design is first step and crucial for success of the beamline !

→ Fundamental of X-ray beamline; light source, monochromator, mirror,...

Beamline structure

Beamline = "Bridge" between light source & experimental station



→ **Transport and processing of photons**

photon energy, energy resolution,

beam size, beam divergence, polarization,..

→ **Vacuum**

protection of ring vacuum and beamline vacuum

→ **Radiation safety**

Shielding and interlock

Monochromator, mirror

shutter, slit

pump,..

Light sources & X-ray optics

Check points to be considered for your application:

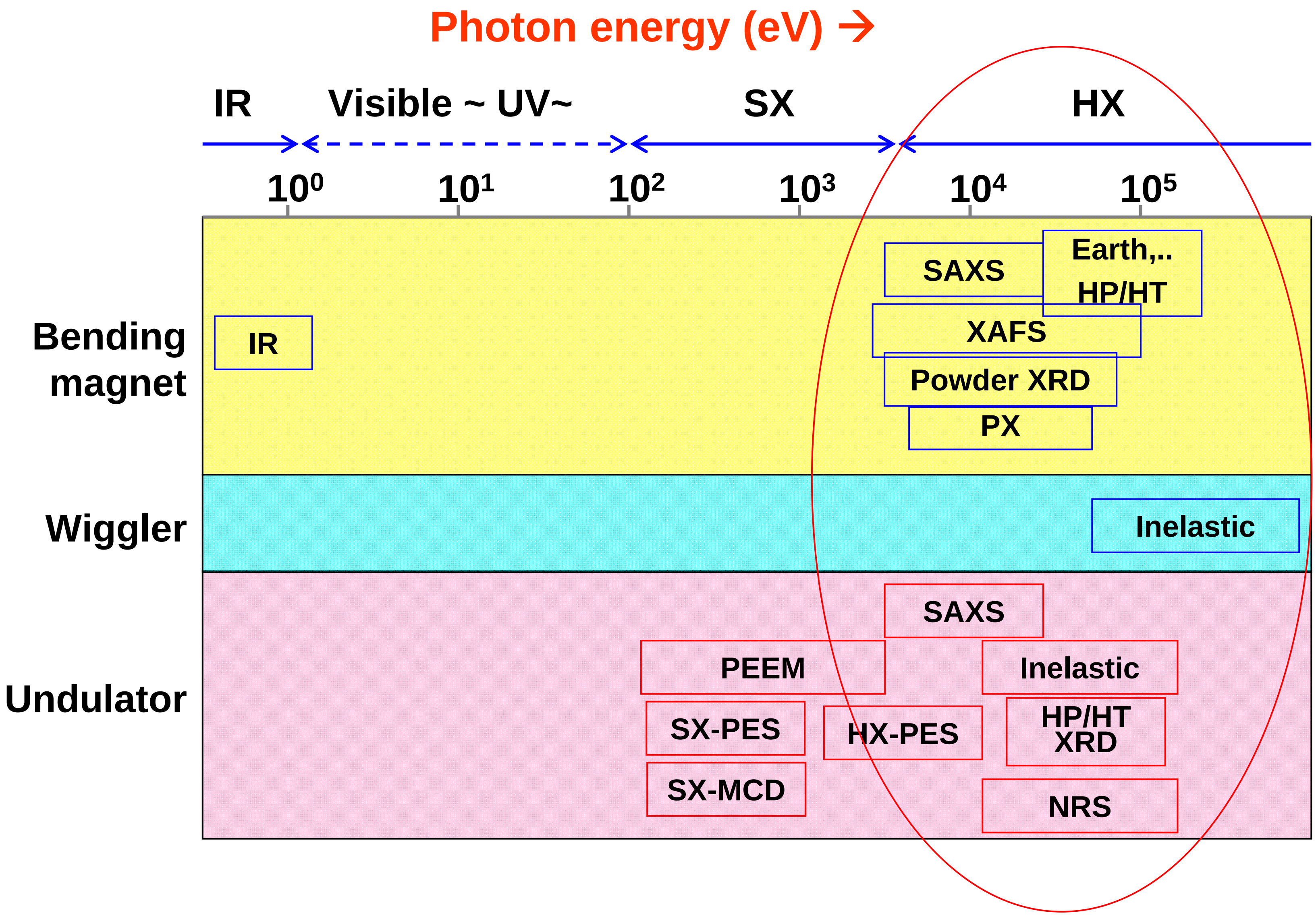
- White or monochromatic
- Energy range
- Energy resolution
- Flux & flux density
- Beam size at sample (micro beam?,...)
- Beam divergence/convergence at sample
- Higher order elimination w/ mirror
- Polarization conversion
- Spatial coherency

....

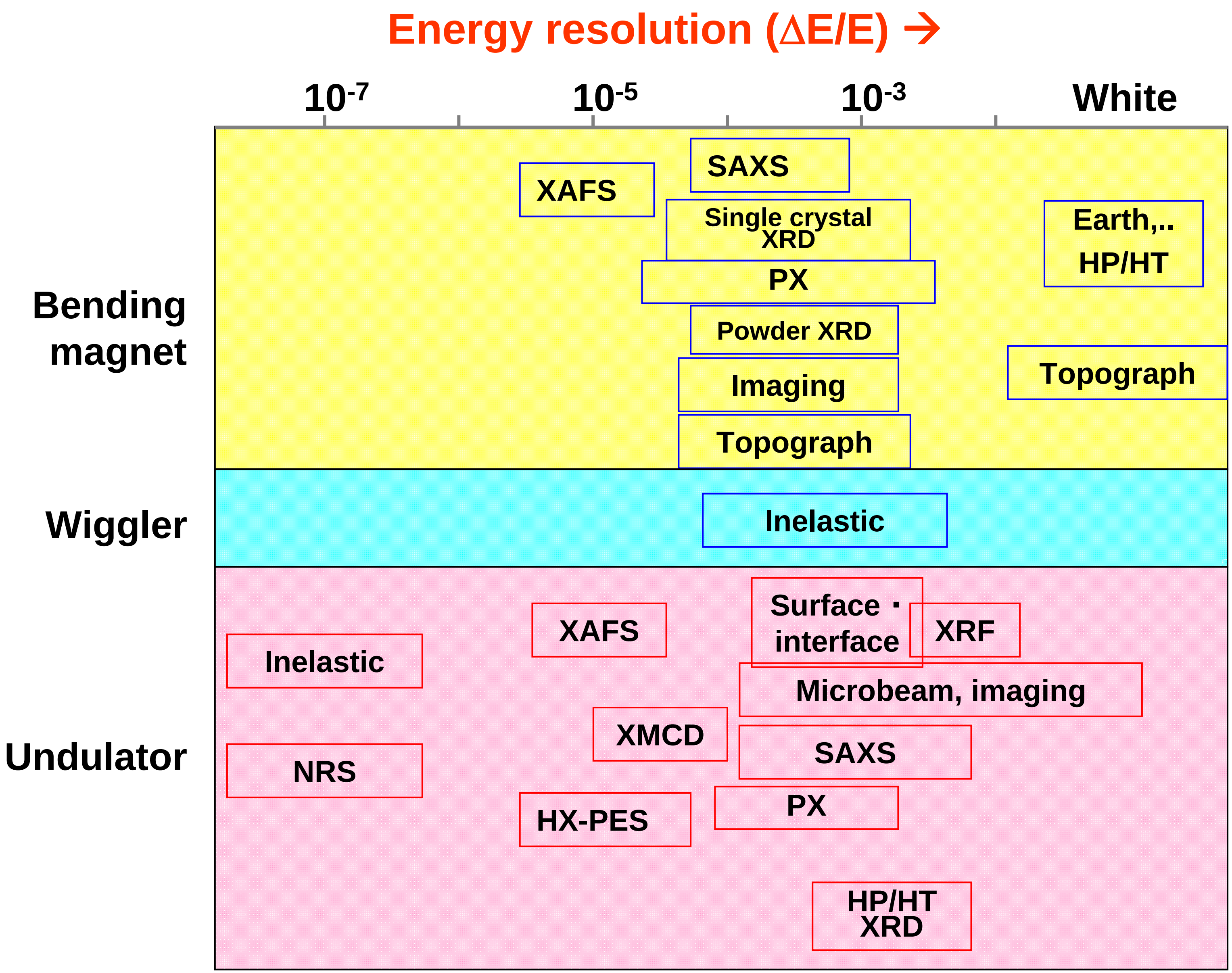
→ Light source, monochromator, mirror,

and other optical devices and components

BL classification (energy region)



BL classification (energy resolution)



Light sources

Bending magnet or insertion devices ?

Bending magnet:

for wide energy range, continuous spectrum

for wide beam application for large samples

Undulator (major part of 3GLS beamline):

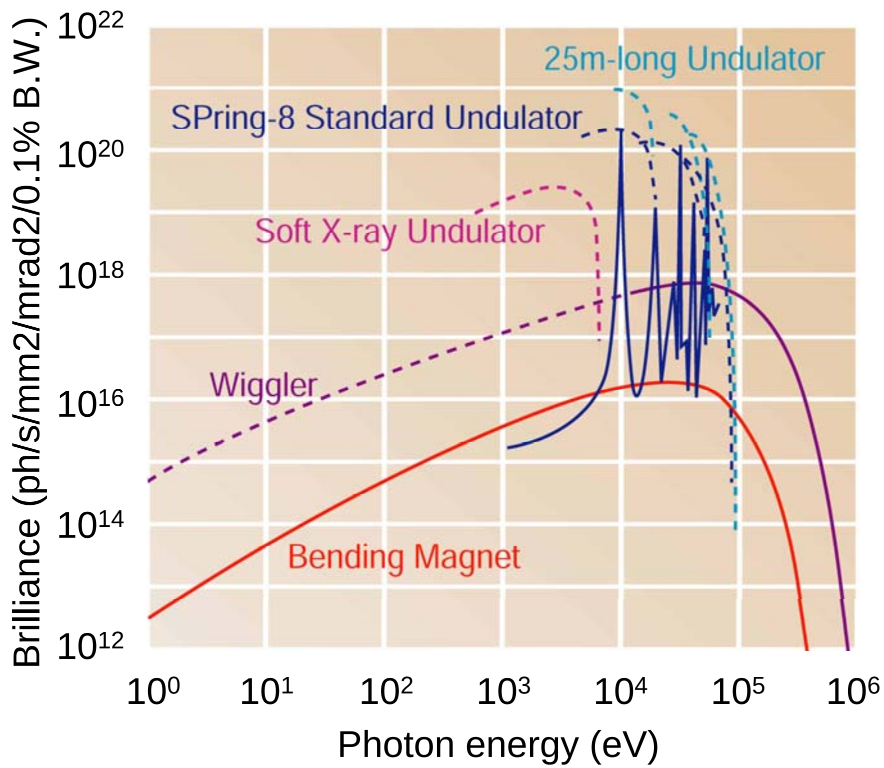
for high-brilliance beam

for micro-/ nano-focusing beam

Wiggler:

for higher energy X-rays > 100 keV.

→ short-period-length undulator



Brilliance for SPring-8 case

Power, brilliance, flux density, partial flux,.. can be calculated using code.

e.g. "SPECTRA" by T. Tanaka & H. Kitamura

Monochromator

Key issues from experimental request:

White or monochromatic ? → monochromatic

Energy region ← Bragg's law

Energy resolution ← Source divergence, Darwin width,..

Throughput ← related to energy resolution

Double-crystal monochromator for fixed-exit

Single-bounce monochromator is for limited case

Heat load ← depending on light source

X-ray monochromator using perfect crystal

→ Principle of monochromator

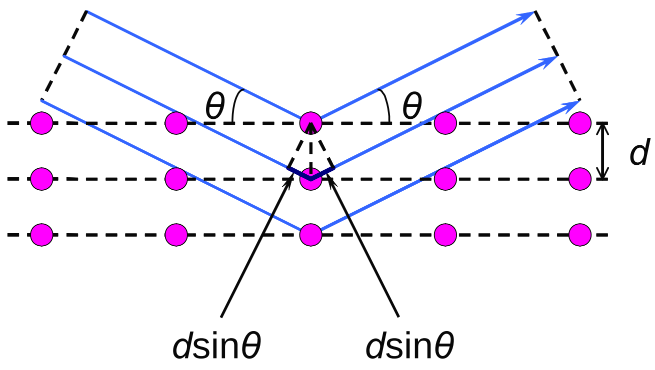
Bragg reflection from perfect single crystal

$$2d \sin \theta_B = n \lambda$$

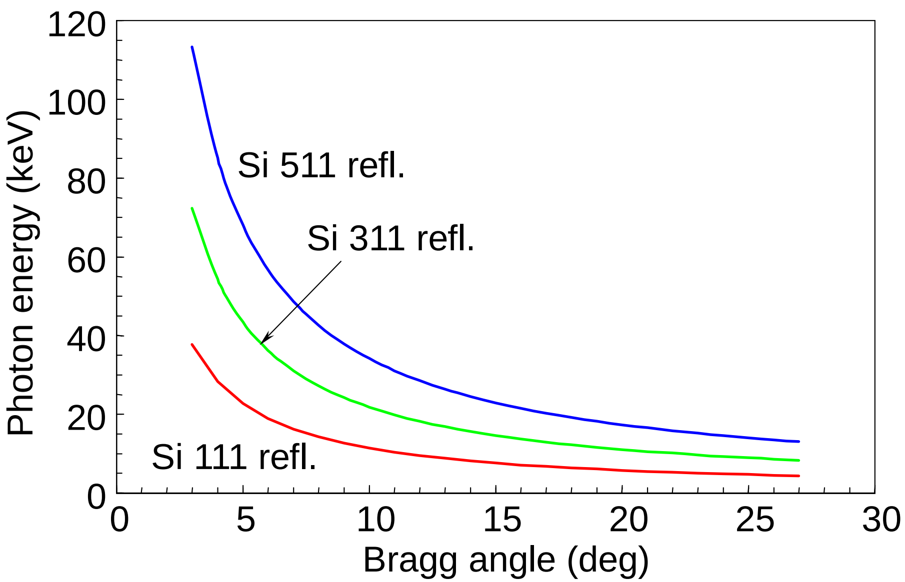
d: Latiice (d)-spacing,

θ_B: glancing angle (Bragg angle),

λ: X-ray wavelength



→ Crystal: silicon, diamond,..



e.g. for SPring-8 standard DCM

Bragg angle: 3~27°

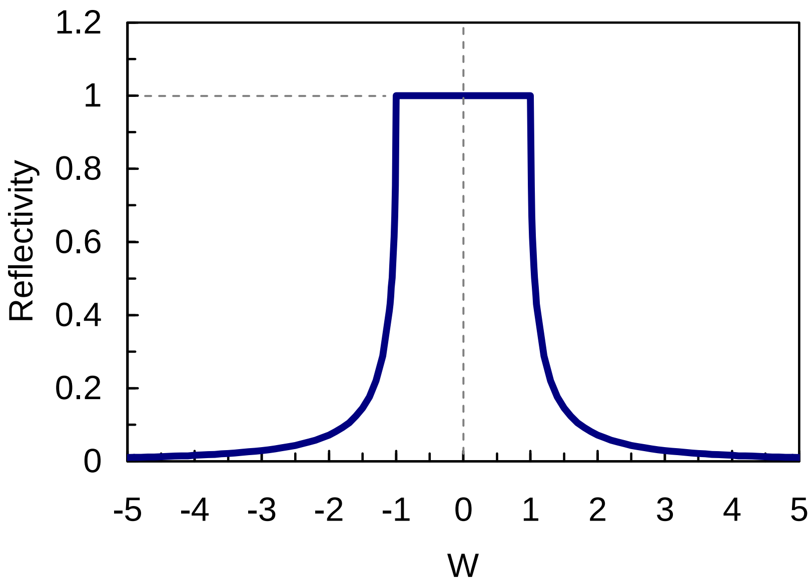
Photon energy range:

- Crystal & lattice plane
- Bragg angle range

Reflectivity (intrinsic rocking curve)

Darwin curve (intrinsic rocking curve for monochromatic plane wave) for Bragg case, no absorption, and thick crystal:

$$
\begin{cases}
R = \dfrac{|\gamma_h|}{\gamma_0}\left|\dfrac{E_h}{E_0}\right|^2 = \left(W + \sqrt{W^2 - 1}\right)^2 & (W < -1) \\
R = 1 \quad (-1 \le W \le 1) & \leftarrow \text{Total reflection region} \\
R = \left(W - \sqrt{W^2 - 1}\right)^2 & (W > 1)
\end{cases}
$$



For symmetric Bragg case, sigma polarization:

$$W = \left\{\Delta\theta \sin 2\theta_{BK} + \chi_{0r}\right\}\frac{1}{|\chi_{hr}|}$$

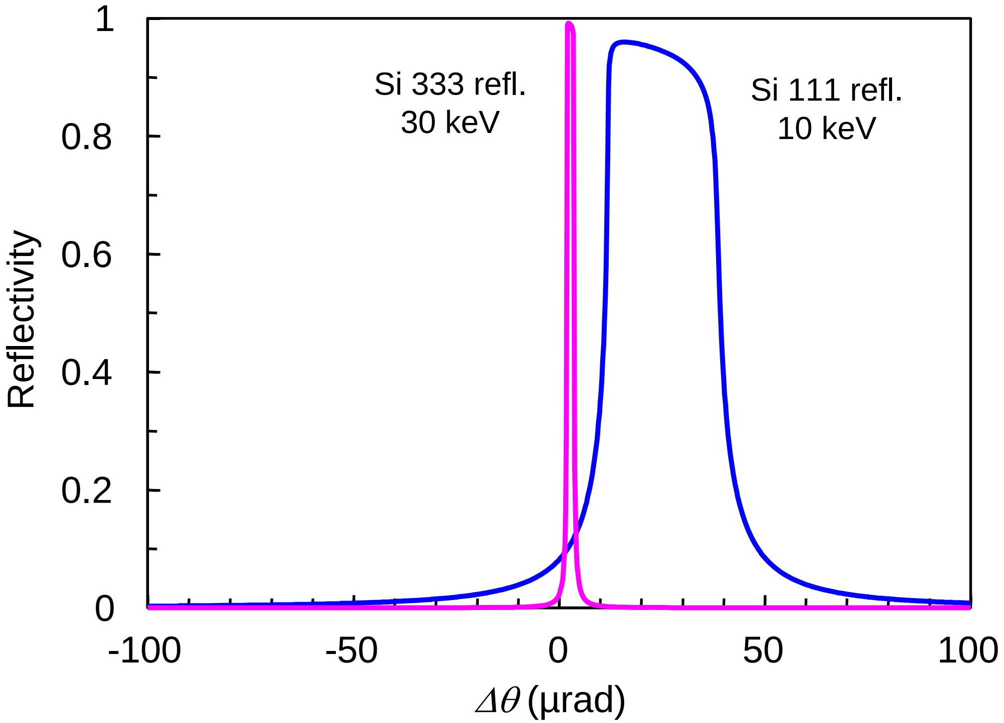
Darwin width → $\Delta W = 2$

$$\omega = \frac{2|\chi_{hr}|}{\sin 2\theta_{BK}} \propto |F_h|$$

Crucial for energy resolution and throughput!

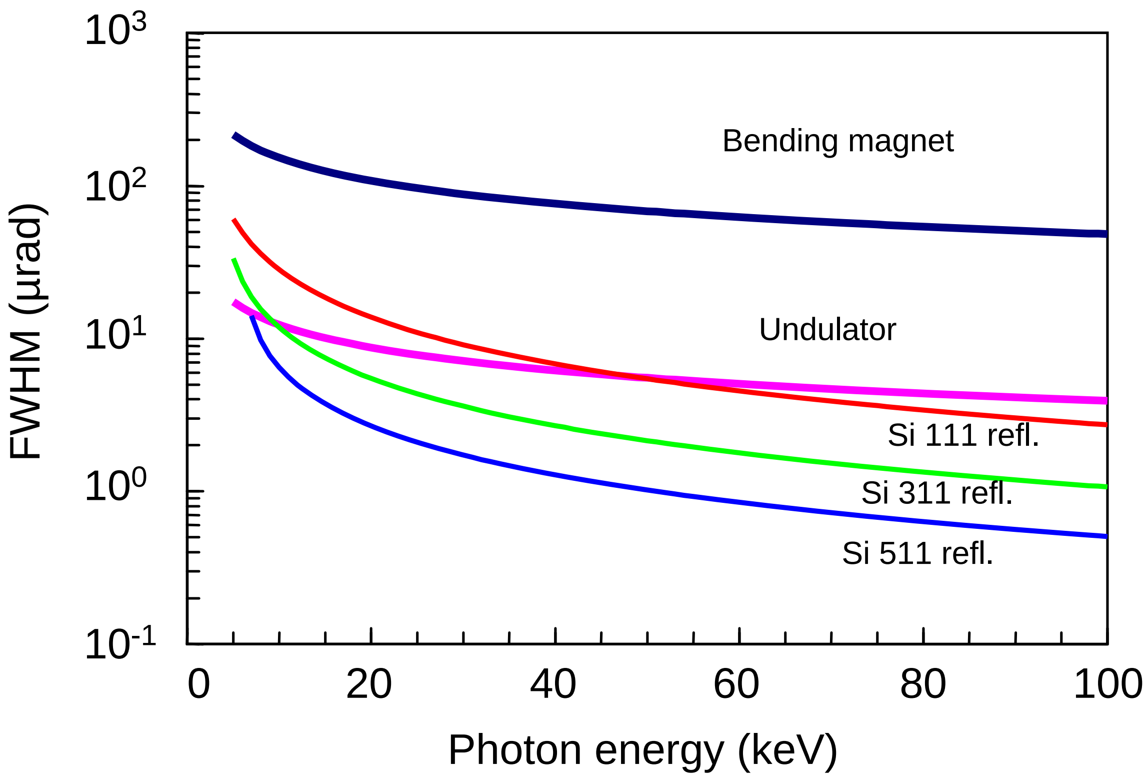
Intrinsic rocking curve for silicon

For Bragg case, with absorption, and thick crystal:



- Darwin width of 0.1～100 μrad
- Peak ~1 with small absorption

Source divergence and diffraction width



Natural divergence

- Bending magnet

$$\sigma_{r'} \approx 0.597 \frac{1}{\gamma}\sqrt{\frac{\lambda}{\lambda_c}} \propto \sqrt{\frac{1}{\hbar\omega}}$$

- Undulator

$$\sigma_{r'} \approx \frac{1}{\gamma}\sqrt{\frac{\lambda}{N\lambda_u}} \propto \sqrt{\frac{1}{\hbar\omega}}$$

For SPring-8 case:

- Bending magnet

$$\sigma_{r'} \approx 60\,\mu\text{rad}$$

- Undulator (*N*= 140)

$$\sigma_{r'} \approx 5\,\mu\text{rad}$$

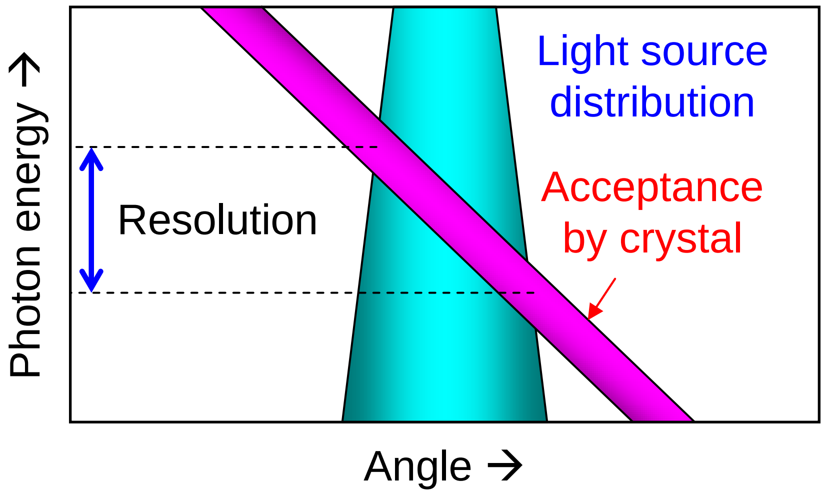
Divergence of undulator radiation ~ diffraction width

Energy resolution

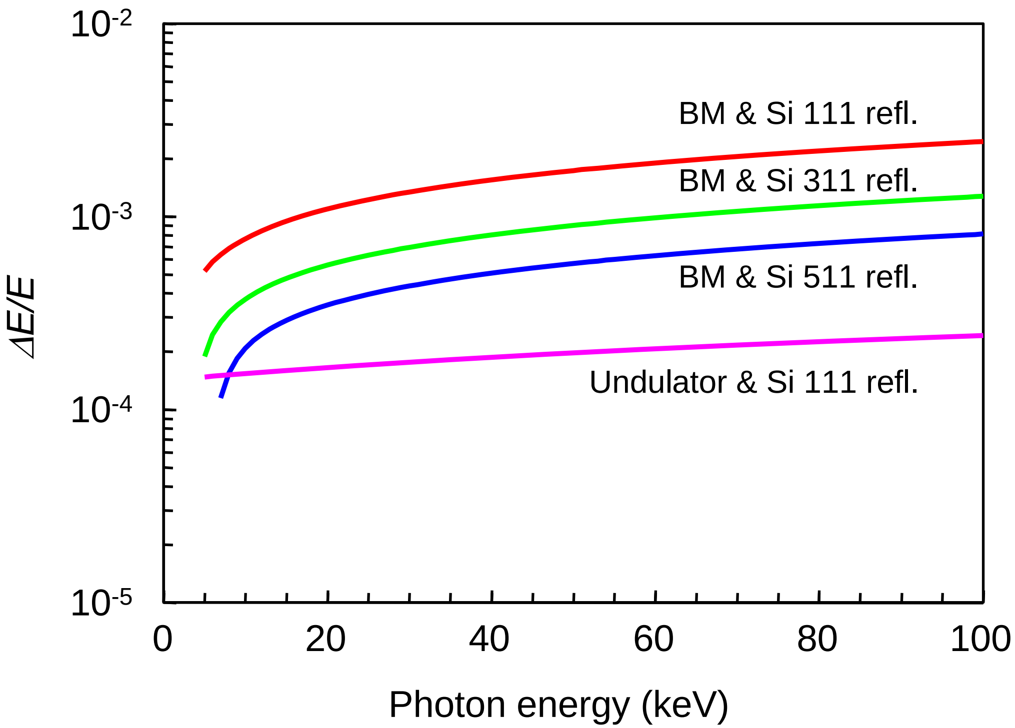
$$\frac{\Delta E}{E} = \cot\theta_B \sqrt{\Omega^2 + \omega^2}$$

Ω: source divergence,

ω: diffraction width

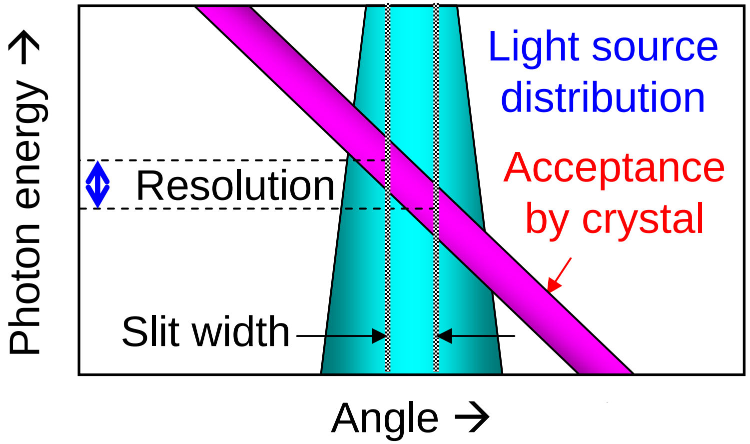


Angle-energy diagram
(DuMond diagram)

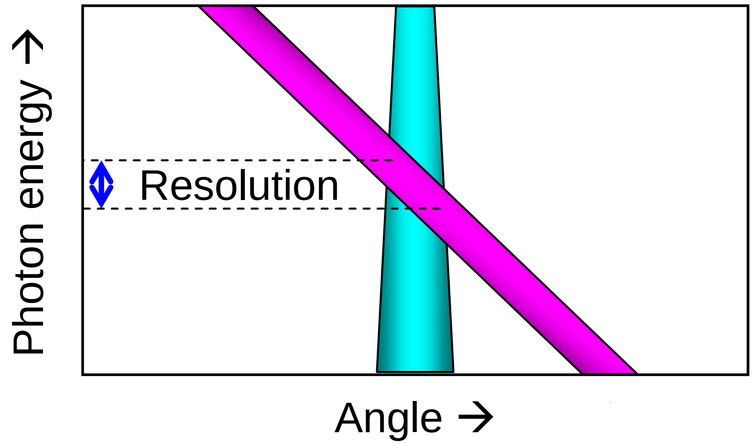


For usual beamline : $\Delta E/E = 10^{-5} \sim 10^{-3}$

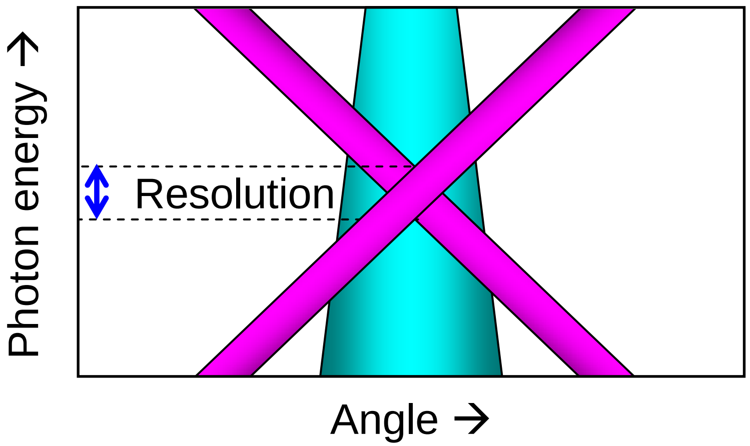
Improvement of energy resolution



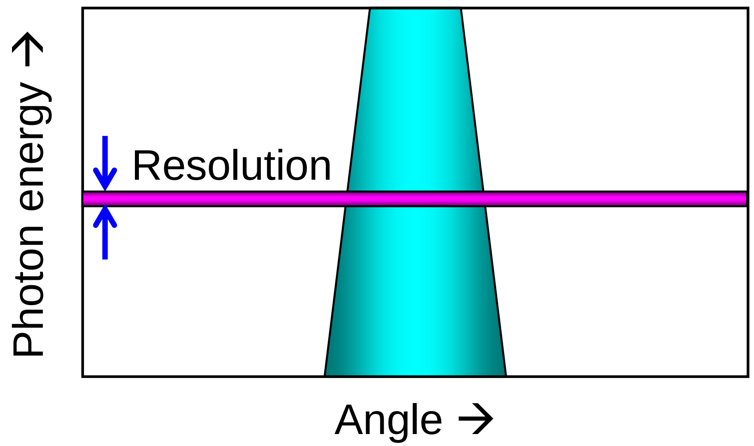
(A) Collimation using slit



(B) Collimation using pre-optics w/ collimation mirror, CRL,..



(C) Additional crystal w/ (+,+) setting



(D) HR monochromator of π/2 reflection (~meV)

(B)~(D): restriction on photon energy

Photon flux after monochromator

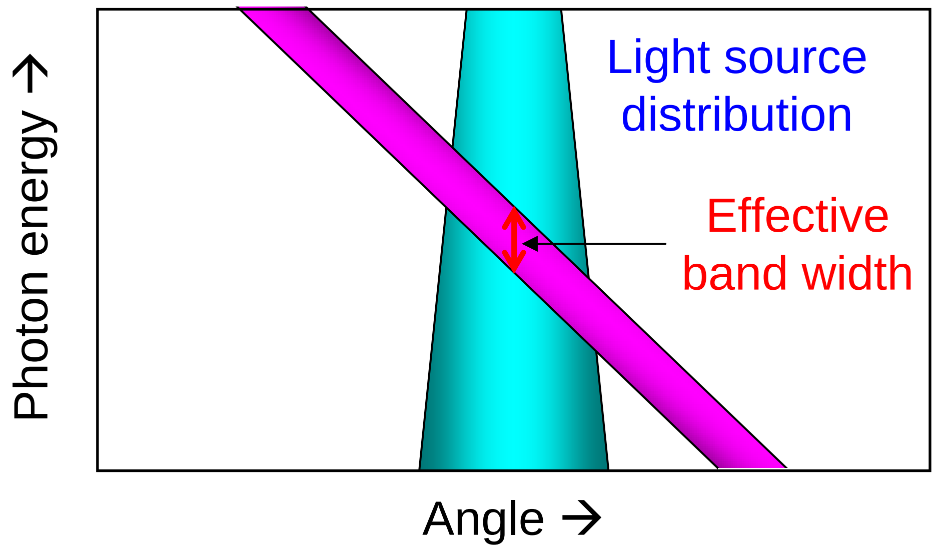
Photon flux (throughput) after monochromator can be estimated using effective band width:

Photon flux (ph/s) =

Photon flux from light source (ph/s/0.1%bw)

x 1000

x Effective band width of monochromator



Throughput is estimated by overlapped area.

Note difference from energy resolution.

Darwin width → energy width

Starting with Darwin width and neglecting anomalous scattering factor *f'*

$$\chi_{hr} \propto \lambda^2 f_0(d_{hkl})$$

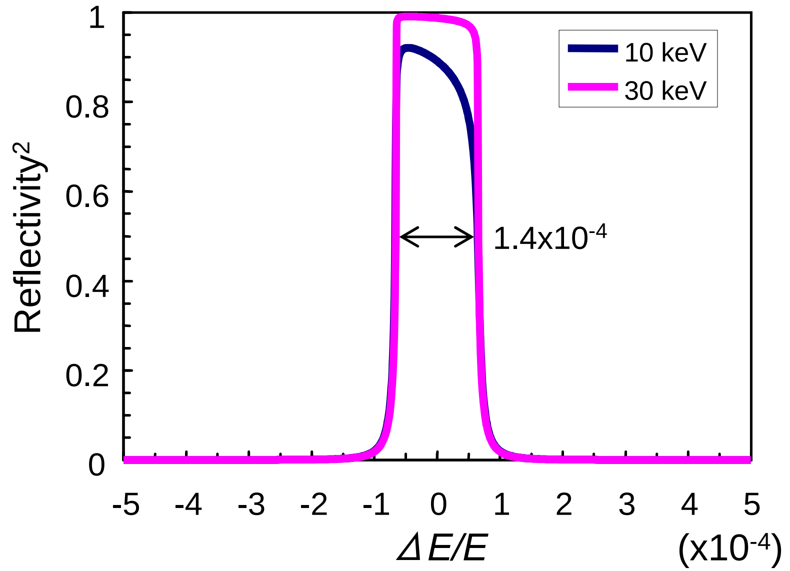
$$\frac{\Delta\lambda}{\lambda} = \omega \cot\theta_B = \frac{2|\chi_{hr}|}{\sin 2\theta_B}\cot\theta_B$$

$$\frac{\Delta\lambda}{\lambda} = \frac{|\chi_{hr}|}{\sin^2\theta_B} = 4{d_{hkl}}^2 \frac{|\chi_{hr}|}{\lambda^2}$$

Energy width:

$$\frac{\Delta E}{E} = -\frac{\Delta\lambda}{\lambda} \propto {d_{hkl}}^2 f_0(d_{hkl})$$

Independent of photon energy



e.g. for Si 111 refl. DCM case

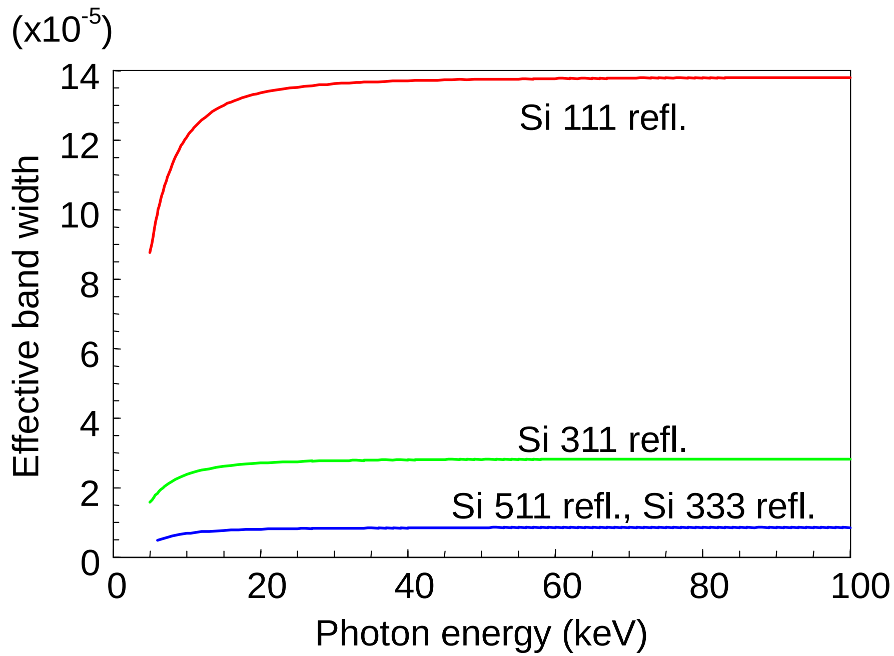
Note relative energy width is constant.

Effective band width (Integrated intensity)

For double-crystal monochromator

$$\left(\frac{\Delta E}{E}\right)_{\mathrm{Eff}} = \frac{|\chi_{hr}|}{2\sin^2\theta_{\mathrm{BK}}} \int R(W)^2 \, dW$$

= ~2

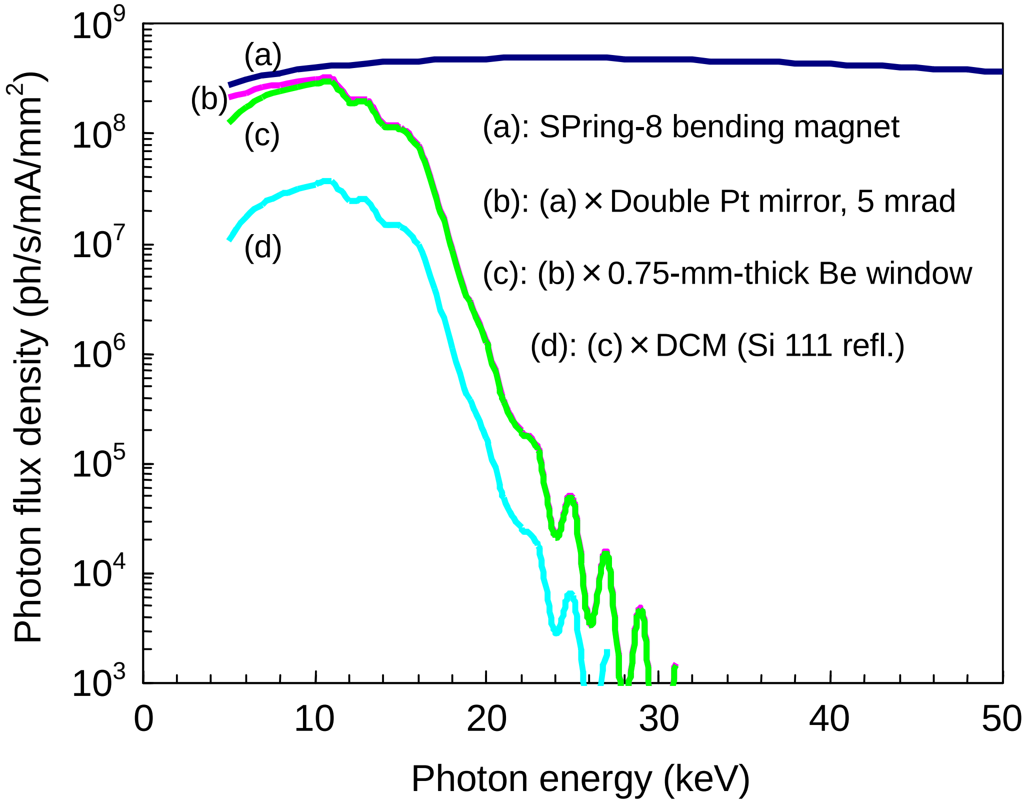


Effective band-width is obtained by integration of rocking curve.

When you need flux → Lower order (Si 111 refl.,..)

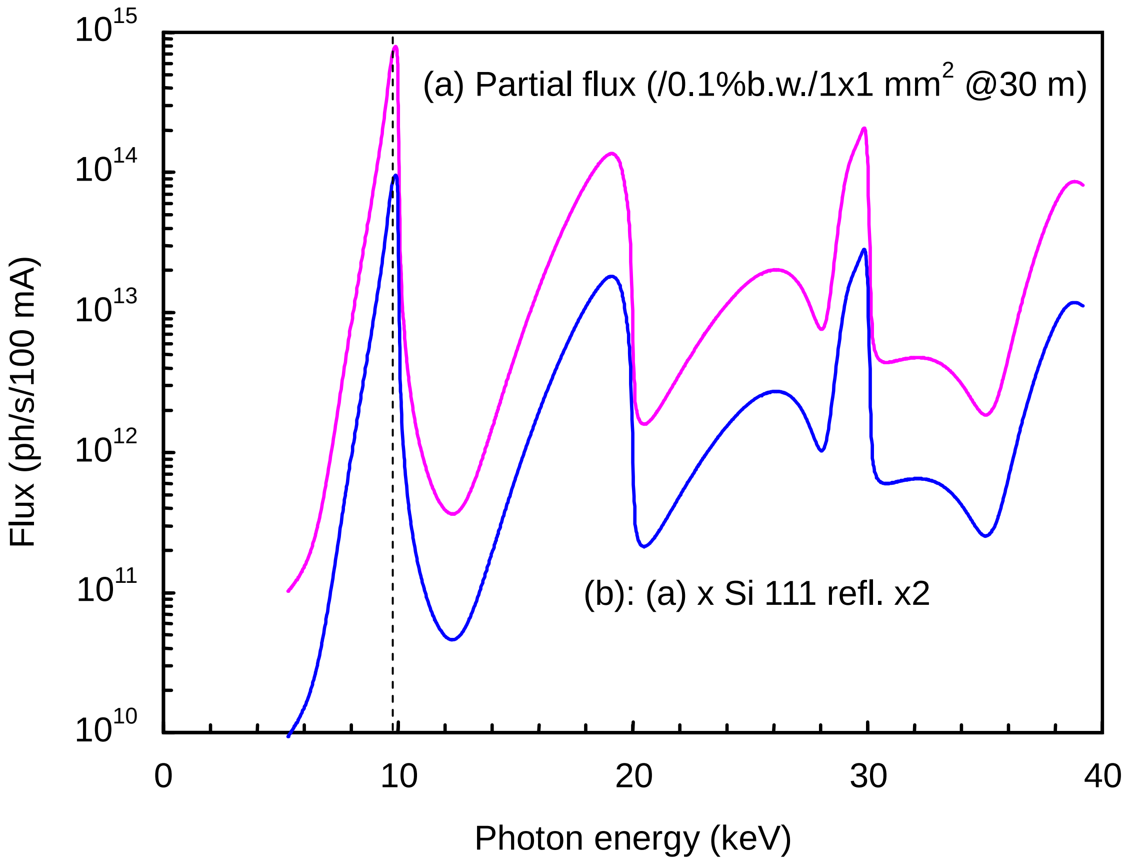
When you need resolution → Higher order (Si 311, Si 511 refl,..)

Photon flux at bending magnet beamline



Example of photon flux estimation at bending magnet beamline BL02B1. (Photon flux density at 50 m from the source)

Photon flux at undulator beamline



We can obtain photon flux of 10^{13}～10^{14} ph/s/100 mA/mm^2 using standard undulator sources and Si 111 reflections at SPring-8 beamlines.

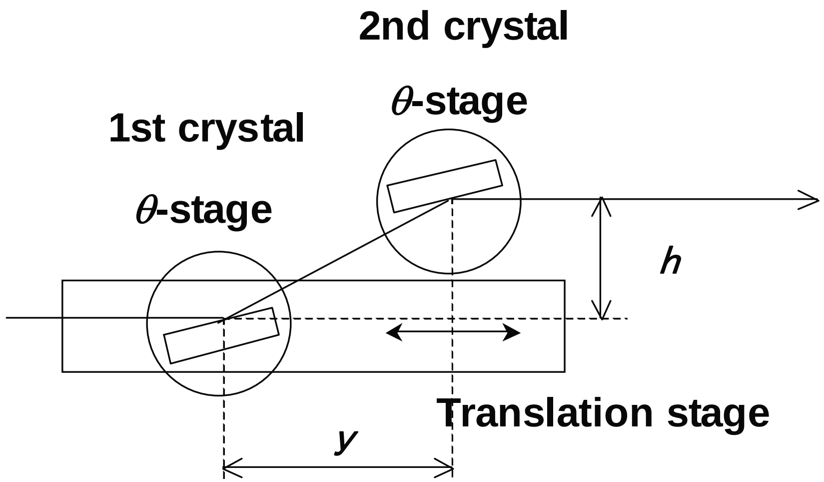
Double-crystal monochromator

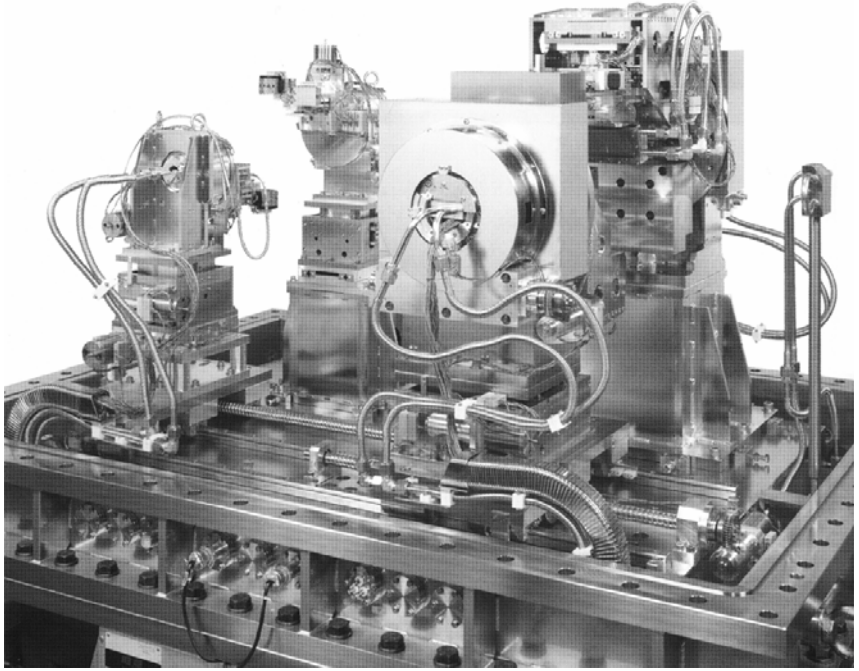
Fixed-exit operation for usability at experimental station.

Choose suitable mechanism for energy range
(Bragg angle range).

Precision, stability, rigidity,...

θ_1 + translation + θ_2 computer link





SPring-8 BL15XU

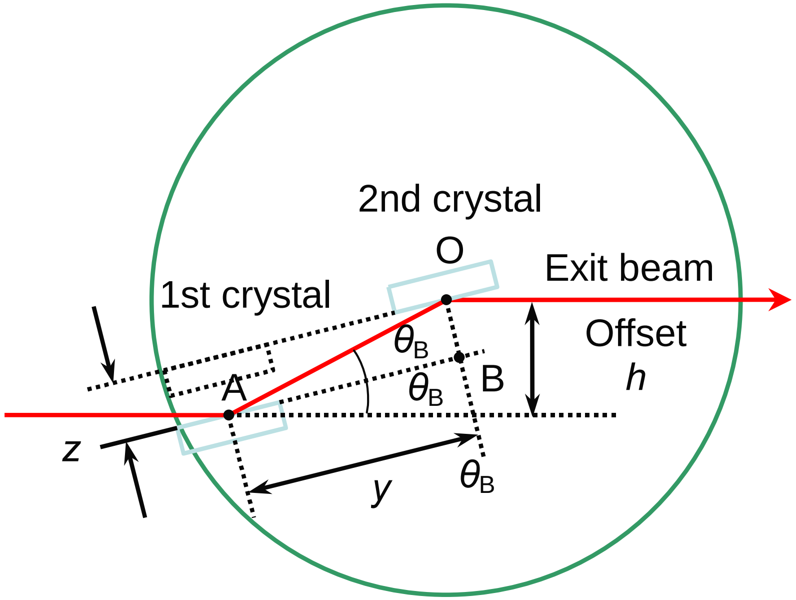
SPring-8 information Vol. 5, No.1 (2000)

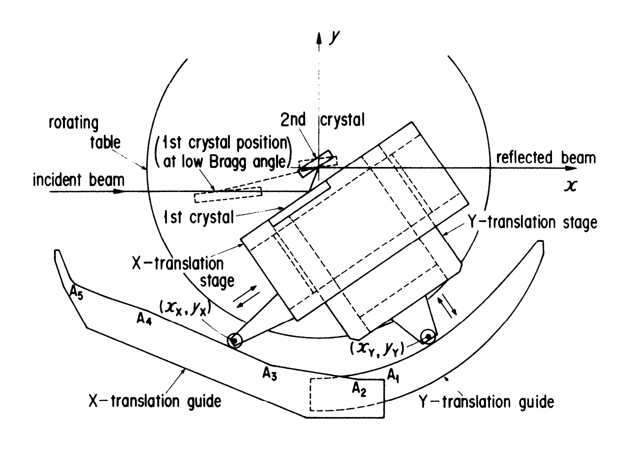
h= 100 mm, θ_B= 5.7~72° (for lower energy range)

Large offset, long-stroke translation

Difficulty of adjustment between 1st and 2nd crystal

θ + two translation (KEK-PF)





PF BL-4C..

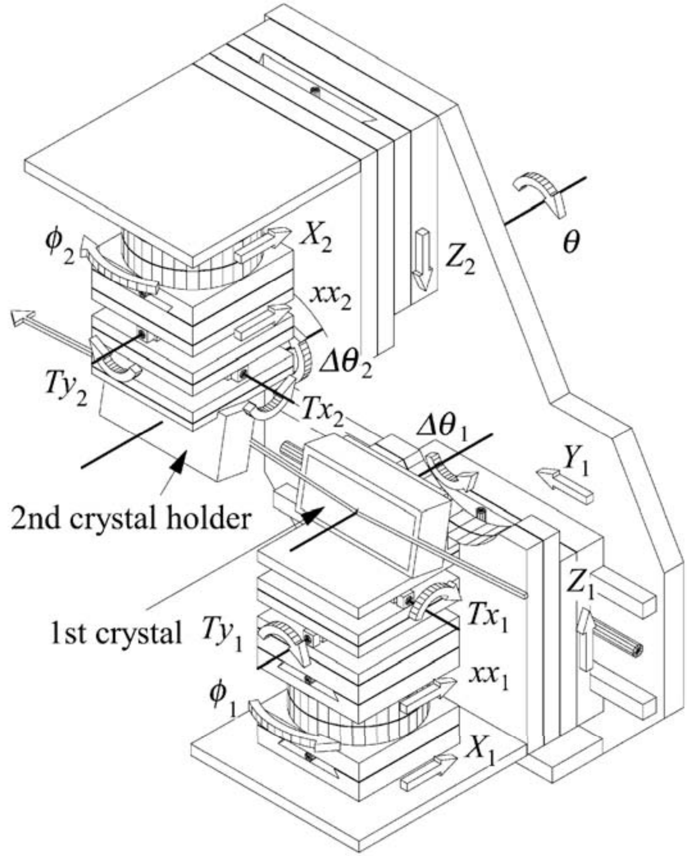
Matsushita et al., NIM A246 (1986)

h= 25 mm, θ_B= 5~70°

Two cams for two translation-stages

Rotation center at 2nd crystal

SPring-8 standard DCM



Offset h= 30 mm

θ_B =3~27º for higher energy range

High-precision adjustment stages

for undulator beamline DCM

Sub-μm & sub-μrad control

Crystal cooling

Why crystal cooling？

Qin (Heat load by SR) = Qout (Cooling + Radiation,..)

→ with temperature rise ΔT

→ $\alpha \Delta T = \Delta d$ (d-spacing change)

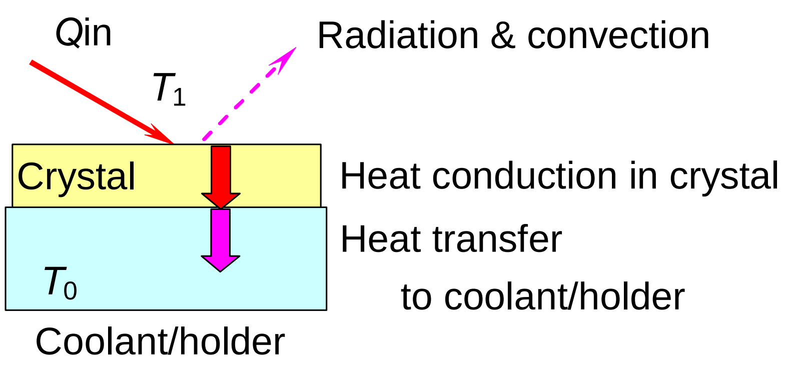
α: thermal expansion coefficient

or → $\Delta \theta$ (bump of lattice due to heat load)

Miss-matching between 1st and 2nd crystals occurs:

→ Thermal drift, Loss of intensity, Broadening of beam, loss of brightness

→ Melting or limit of thermal strain → Broken !



Solution for crystal cooling

We must consider:

Thermal expansion of crystal: α,

Thermal conductivity in crystal: κ,

Heat transfer to coolant and crystal holder.

Solutions:

(S-1) κ / α → Larger

(S-2) Large contact area between crystal and coolant/holder

→ larger

(S-3) Irradiation area → Larger, and power density → smaller

Figure of merit

	Silicon 300 K	Silicon 80 K	Diamond 300 K
κ (W/m/K)	150	1000	2000
α (1/K)	2.5×10^{-6}	-5×10^{-7}	1×10^{-6}
κ / α $\times10^{6}$	60	2000	2000

Figure of merit of cooling:
Good for silicon (80 k) and diamond (300 K)

For SPring-8 case

Bending magnet beamline

Power and density : ~100 W, ~1 W/mm^2 @40 m

Method:

→ Direct cooling with fin crystal ← S-2

Undulator beamline

(Linear undulator, N= 140, λu= 32 mm)

Power and density : ~500 W , ~500 W/mm^2 @40 m

Methods:

→ Direct cooling of silicon pin-post crystal ← S-2

+ Rotated inclined geometry (→10 W/mm^2) ← S-3

→ or Cryogenic cooling using LN_2 circulation ← S-1

→ or Indirect cooling of IIa diamond crystal ← S-1

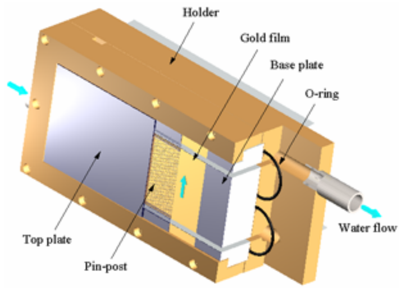
Crystal monochromator at SPring-8

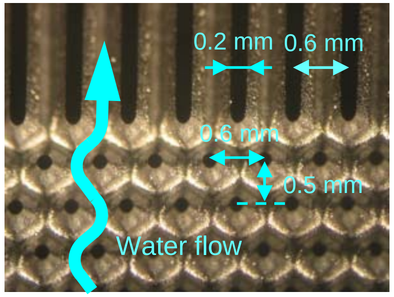
For high heat load undulator beamline

(Linear undulator, *N*= 140, λu= 32 mm)

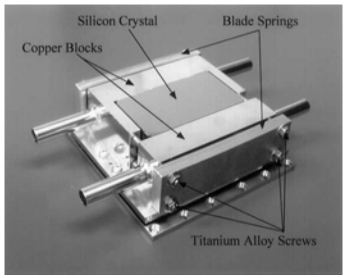
Power and density : ~500 W , ~500 W/mm^2 @40 m

a) Direct cooling of silicon pin-post crystal





b) Silicon cryogenic cooling



c) IIa diamond with indirect water cooling

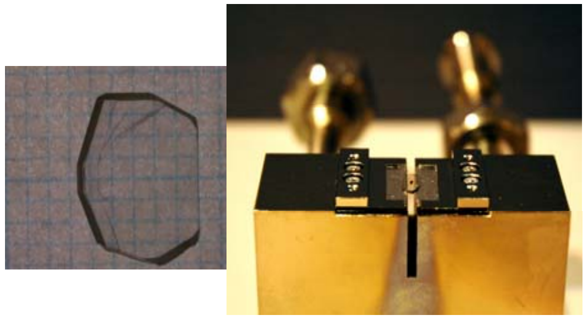


Figure of merit of b and c is almost same.

Mirror

- Higher harmonics rejection

- Bent mirror for focusing/collimation

- *Figured mirror for micro~nanobeam*

Mirror quality

Mirror quality must be considered.

→ Micro-roughness

- Reduction of reflectivity
- Lower-energy shift of critical energy
- Diffuse scattering

Optical (Zygo) range (<1 mm): ~ 0.3 nm rms or less
AFM range (<1 μm): ~ 1 nm rms or less

→ Insufficient coating

- Reduction of reflectivity
- Lower-energy shift of critical energy

Should be ~100%

→ Slope error

- Beam shape deformation
- Wave-front distortion
- Flux density loss

LTP range (<1 m): ~1 μrad or less

Mirror reflectivity

Mirror reflectivity for sigma-polarization:

$$R = \left| \frac{k_{iz} - k_{tz}}{k_{iz} + k_{tz}} \exp(-2 k_{iz} k_{tz} \sigma^2) \right|^2$$

$$k_{iz} = \frac{2\pi}{\lambda} \cos\theta, \; k_{tz} = \frac{2\pi}{\lambda} \sqrt{n^2 - \cos^2\theta}$$

k_{iz}, k_{tz}: Normal components of incidence and transmitted wave vectors

n: complex index of refraction

θ: glancing angle

σ: high-spatial-frequency roughness (AFM region)

Surface roughness must be considered
around critical energy (angle).

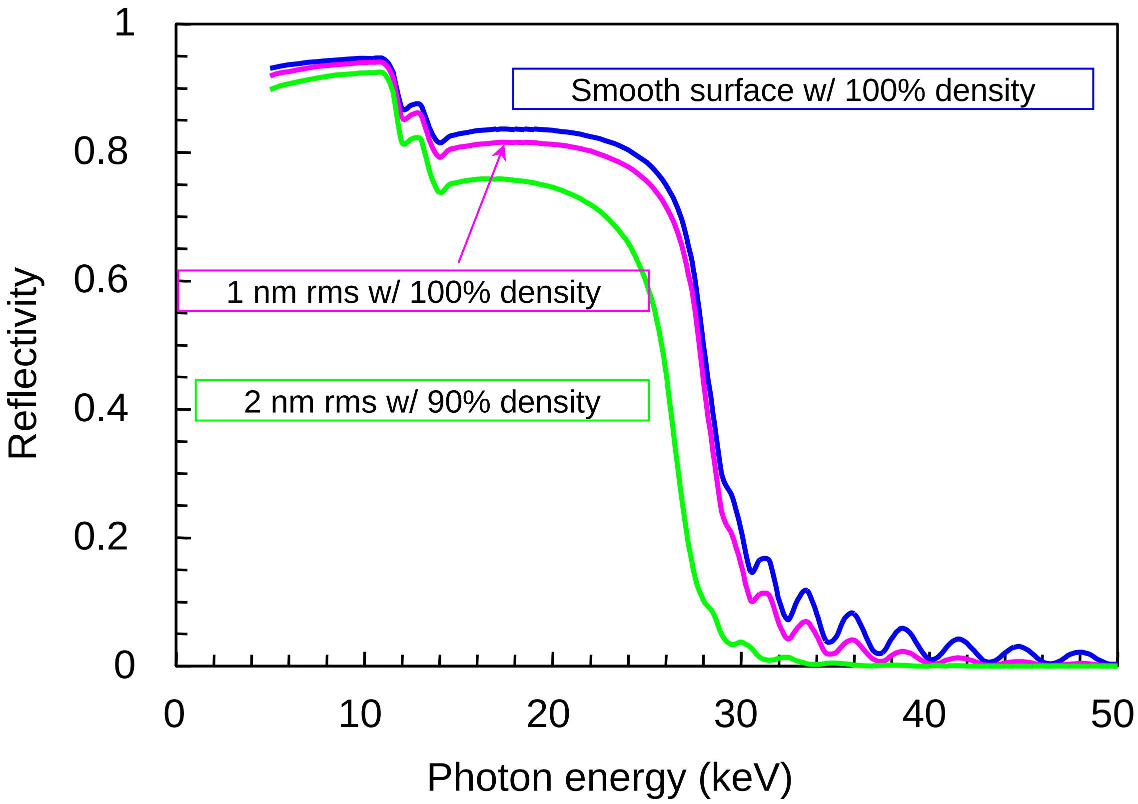
Effect of roughness

e.g. reflectivity of Pt mirror

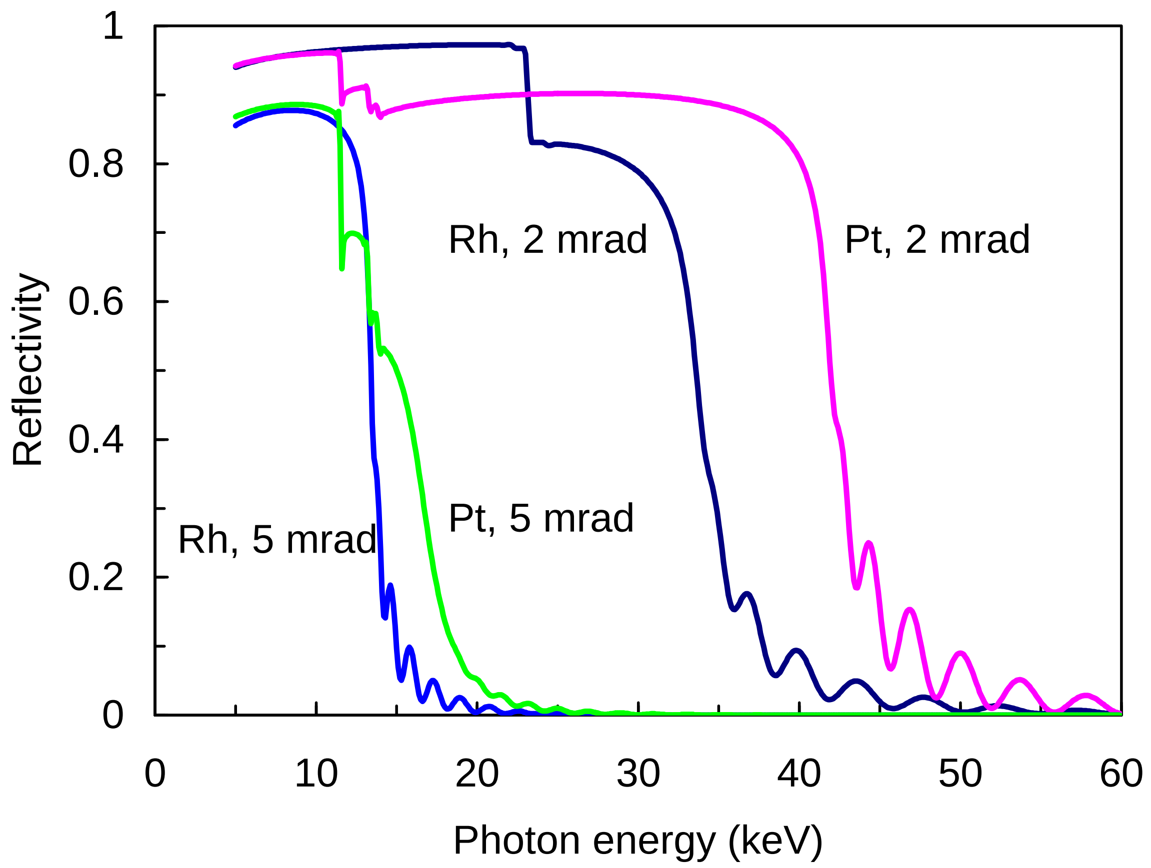
s-polarization

Glancing angle: 3 mrad

Film thickness: 50 nm



Example of mirror reflectivity



Thickness 50 nm, roughness 1 nm

Material, glancing angle, length

❑ Material

Si, SiC for white radiation

SiO_2, Glass,.. for monochromatic beam

❑ Coating

Pt, Rh, Ni,...

Depending on energy, reflectivity, absorption edges,..

❑ Glancing angle

2~10 mrad (For SPring-8 X-ray beamline)

Depending on energy, reflectivity, absorption edges,..

❑ Mirror length

400 mm~1 m (For SPring-8 X-ray beamline)

Depending on the beam size and glancing angle

e.g. 100 μrad × 50 m/5 mrad= 1 m

Focusing with mirror

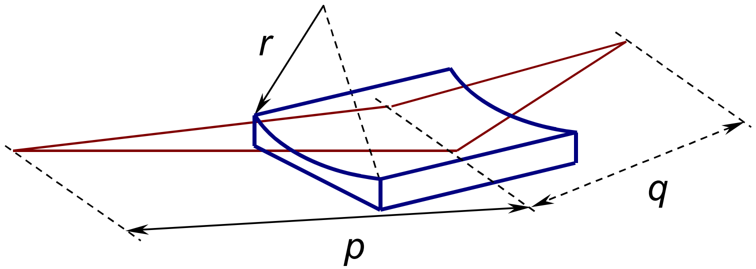
For beam focusing or collimation, we need;

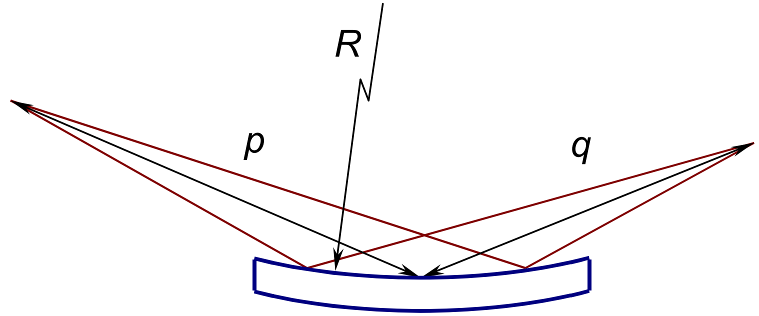
elliptical mirror, ellipsoidal mirror, parabolic mirror, paraboloidal mirror,...

➔We can approximate by bending:

flat → meridional cylinder,

sagittal cylinder → toroidal,...





Sagittal focusing

w/ sagittal cylinder

$$r = \frac{2pq}{p+q}\sin\theta$$

Meridional focusing

w/ meridional cylinder

$$R = \frac{2pq}{(p+q)\sin\theta}$$

e.g.) θ= 5 mrad, p= 40 m, q= 10 m

r= 80 mm, R= 3.2 km

※ When $q\rightarrow\infty$

We obtain parallel beam:

$$r = 2p\sin\theta$$

$$R = 2p/\sin\theta$$

Focusing with mirror

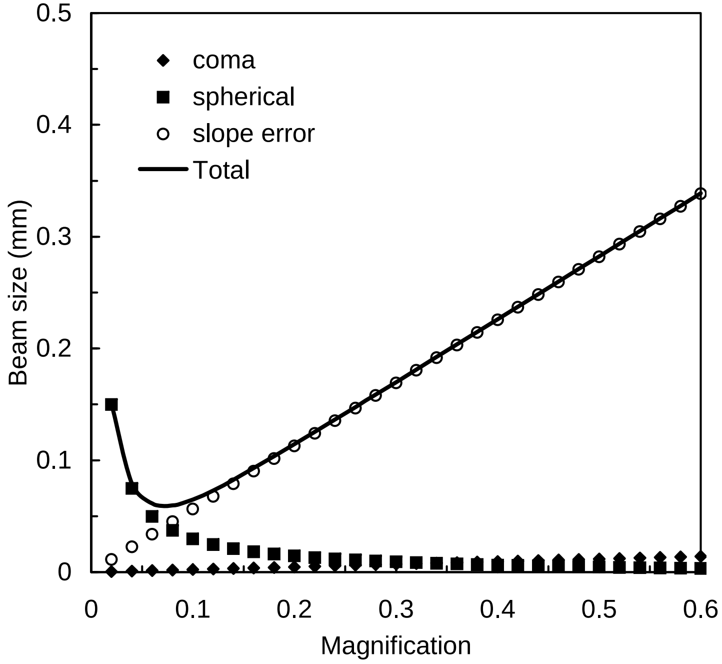
Beam size using meridional cylinder mirror:

$$F_{coma} = 2.35\Sigma M$$

$$F_{spherical} = \frac{3L^2\theta(1-M^2)}{16pM}$$

$$F_{Fabrication} = 2\times 2.35\Delta_{fabrication}Mp$$

$$F_{total} = \left[\left(F_{coma}+F_{spherical}\right)^2 + F^2{}_{fabrication}\right]^{1/2}$$



e.g.

Σ = 10 µm

L = 400 mm

$\Delta_{fabrication}$ = 3 µrad

θ = 4 mrad

p = 40 m

Σ: source size

M: magnification = q/p

L: mirror length

$\Delta_{fabrication}$: slope error

θ: glancing angle

For micro~nonofocusing, we need precisely-polished and large NA elliptical K-B mirror near exp. station.

J. Susini, Opt. Eng. **34**, 361 (1995)

SPring-8 standard mirror support

For SPring-8 X-ray beamline

❑ For undulator beamline

400-mm-long, vertical deflection, plane
700-mm-long, horizontal deflection, plane

❑ For bending magnet beamline

1-m-long, vertical deflection,
plane/cylindrical

Options

- Bender
- Indirect water-cooling (side cooling)

For 400-mm-long mirror,
Vertical deflection, w/ bender

For 1-m-long mirror,
vertical deflection,
w/ bender, Indirect water-cooling

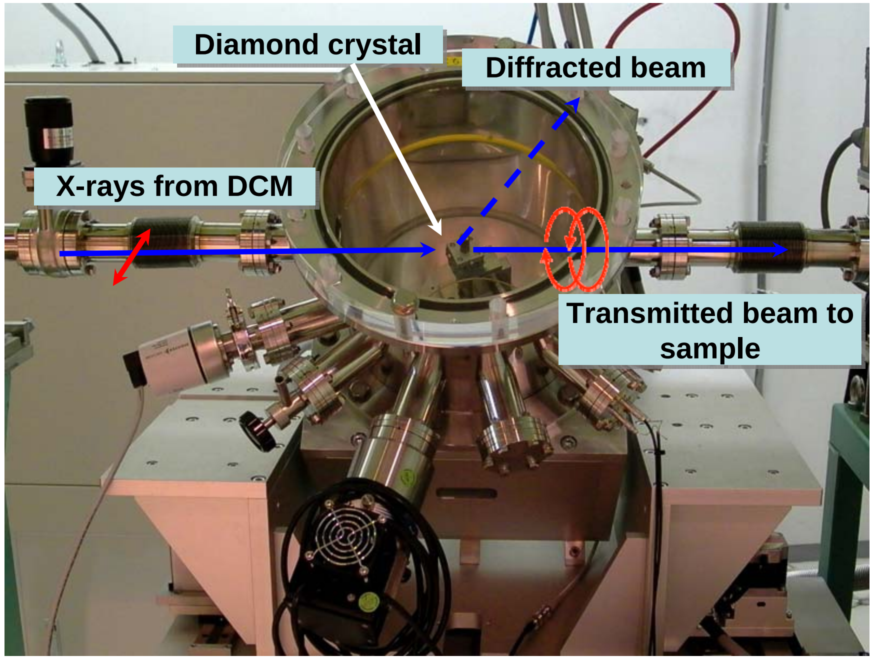
Polarization conversion

Phase retarder is used to convert the polarization for XMCD and other applications.

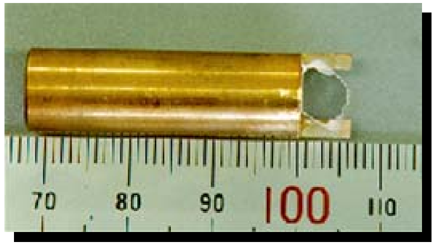
Horizontal polarization → right-/left-circular polarization
Horizontal polarization → vertical polarization
...

Crystal: IIa diamond,..

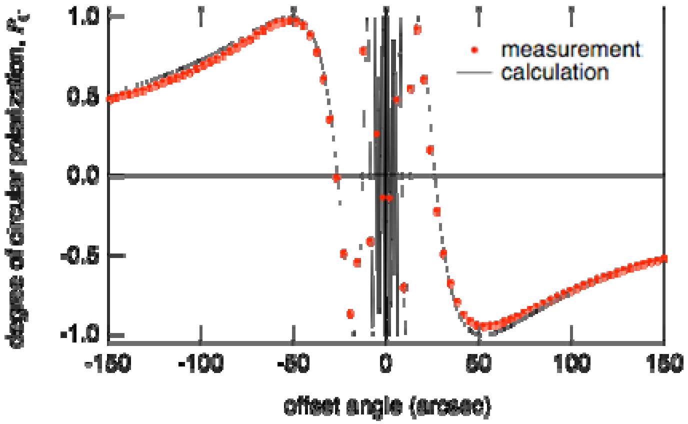
Diamond phase plate system BL39XU

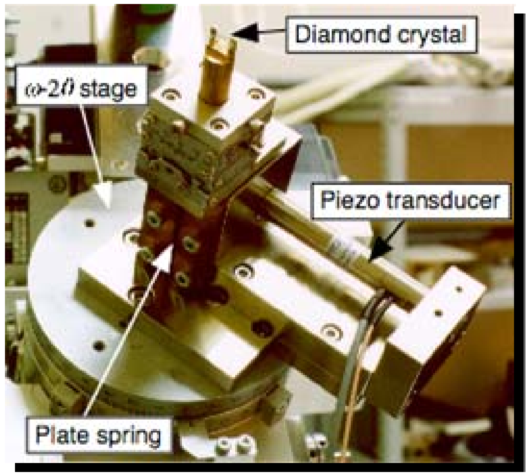


Stages and vacuum chamber of phase retarder



0.45-mm-thick (111) diamond plate





Switcher of phase

Selection of phase plate

Thickness (mm)	Index	Reflection	Energy (keV)	Transmittance (%)
0.34	(111)	111 Bragg	5~5.8	3~7
		220 Laue	5.8~7.5	7~41
0.45	(111)	220 Laue	6~9	5~53
0.73	(111)	220 Laue	8~12	22~65
2.7	(001)	220 Laue	11~16	13~47

Spatial coherence

We need:

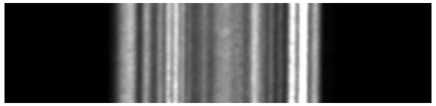
- small source size (σ_s) & long beamline (L)

$$l_{coh} \propto \frac{\lambda L}{\sigma_s}$$

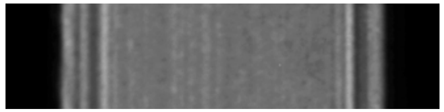
(*depend on machine performance and facility design !*)

- w/ speckle-free optics.

Mirror

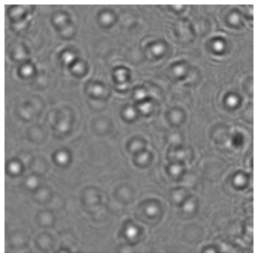


→ultra smooth surface



100 mm

Be window



→void-free & polished

300 μm

e.g. x-ray images using coherent x-rays

Front-end

(1) Vacuum chamber (with ion pumps,..)

Pressure (10^{-7}～10^{-5} Pa)

(2) Main beam shutter (MBS)

・Water-cooled absorber

・Beam shutter

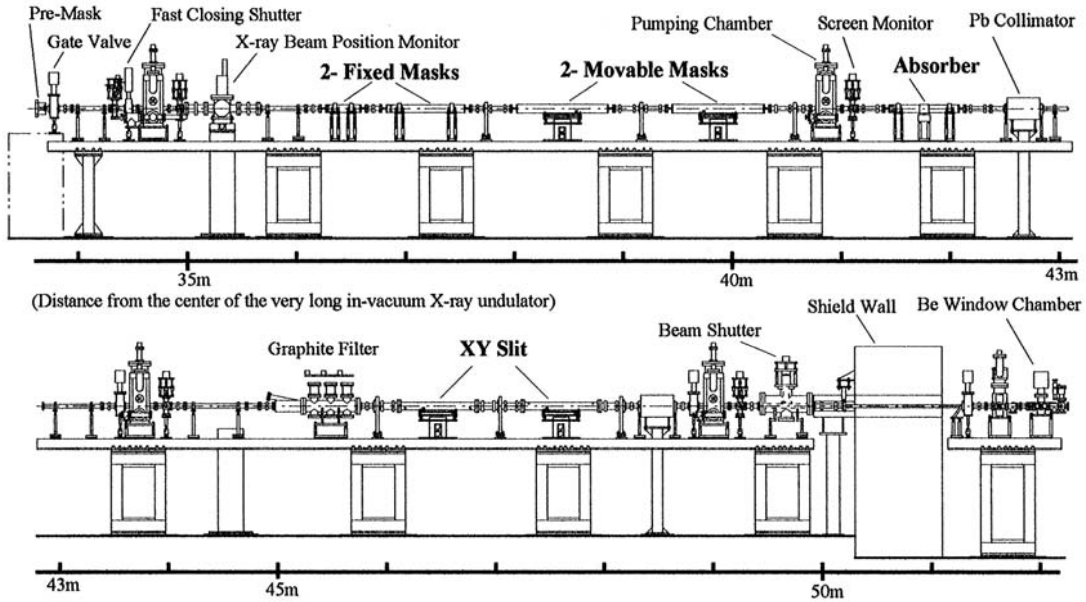
(3) Mask, XY-slit

Spatial power control

(4) Water-cooled Be windows

Protection of UHV

(5) Beam position monitor

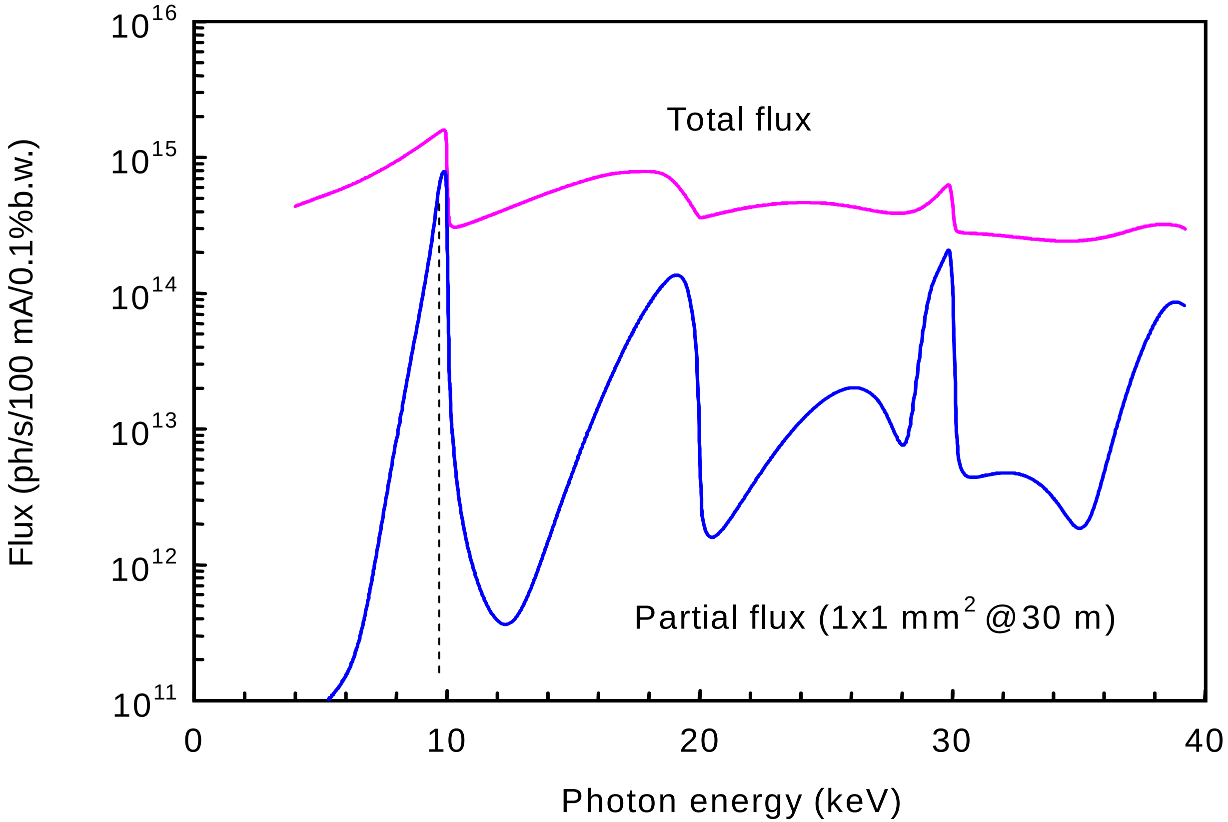


e.g. SPring-8 BL19LXU front-end

It reduces source power of 33 kW down to 500 W for downstream optics

Grazing incidence technique w/ GlidCop
→ 10 kW/m

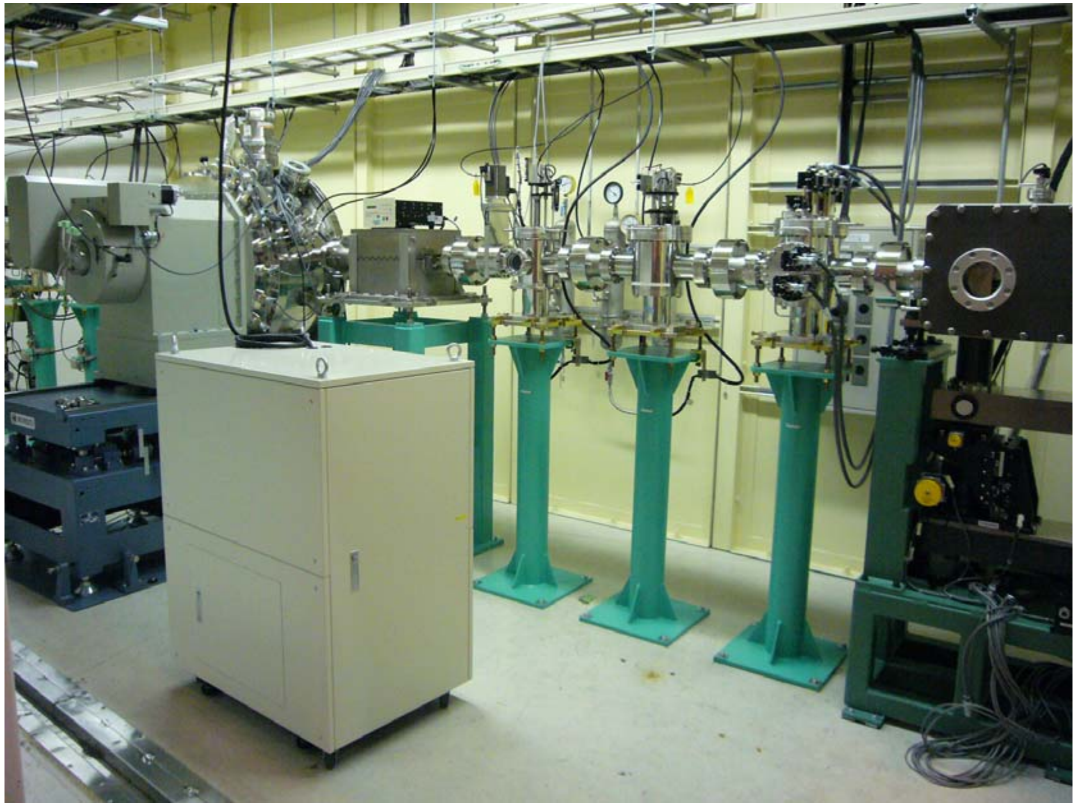
Reduction of power at front-end



e.g. Radiation From standard x-ray undulator λu=32 mm, *N*= 140, fundamental peak of 10 keV

Front-end eliminates the out-of-axis power spatially and reduce the power on the first optical element

Transport channel



e.g. BL14B2

- **Transport channel components**

  Exhaustion unit (ion-pump, TMP,..)

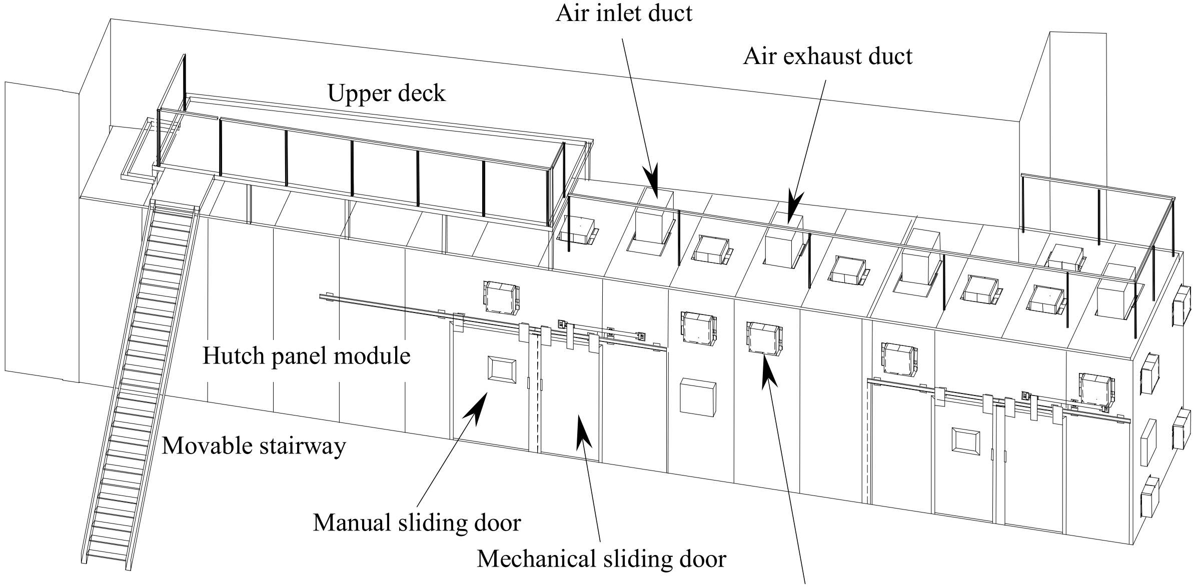
  Down stream shutter (W or Pb)

  Gamma stopper (Pb)

  Beryllium window

  Screen monitor

Shielding hutch @SPring-8



❑**Optics hutch**

contains optics and transport channel components introducing white radiation

❑**Experimental hutch**

contains experimental station equipments introducing monochromatic beam

- Panel — Steel/ Lead/ steel sandwich structure
- Lead thickness — Depends on the radiation condition (3～50 mm)
- Module — Panel, Door, Cable duct, Air inlet/exhaust duct,...
- Utility — Compressed air, Chilled water, electric power

Other issues on beamline design

- Boundary condition

  storage ring and tunnel, neighboring beamline,..

- Radiation safety for shielding hutch, shutter,..

  Radiation shielding calculation (EGS4, STAC8,..)

- Control and interlock

  Common scheme in the facility.

  Connection with machine and safety control

- Others

  Utilities: electricity, water, compressed air, air conditioning.

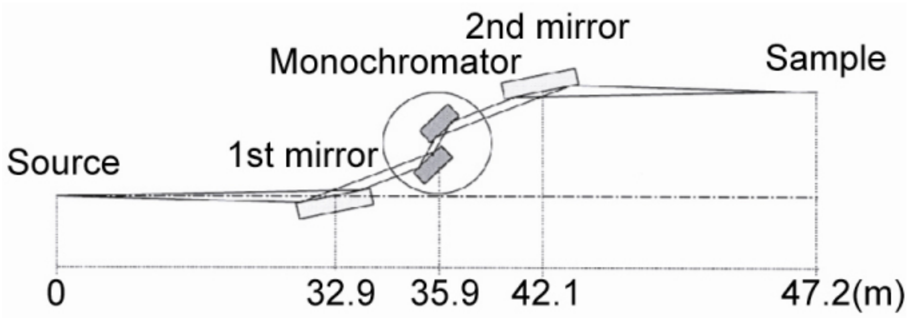
  Environmental: vibration of floor, temperature of air,..

Cooperation with each specialist in the facility is crucial !

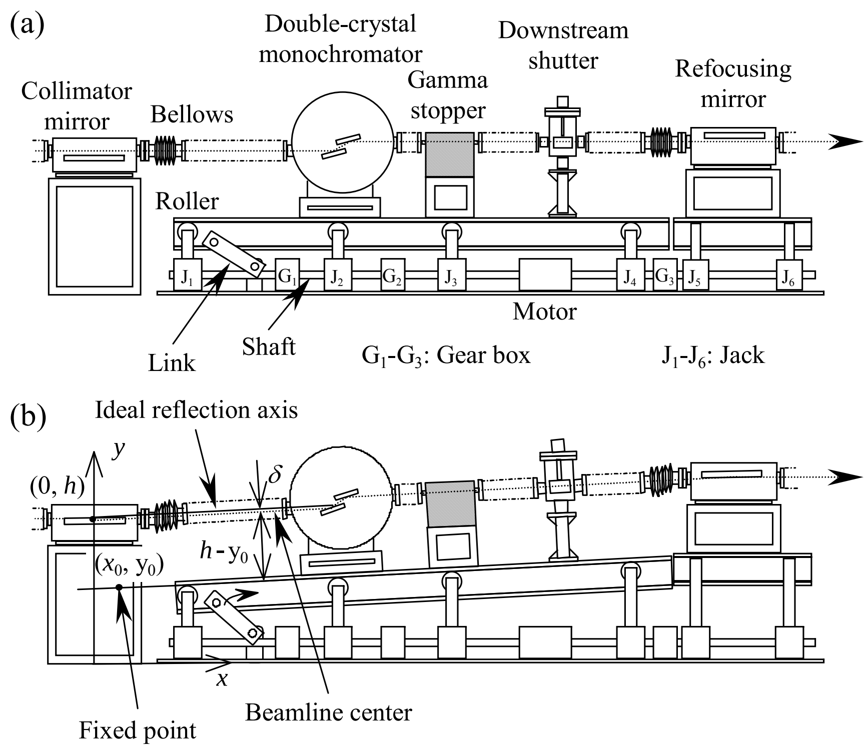
Example of x-ray beamline
- SPring-8 case -

XAFS & single crystal diffraction

- Bending magnet
- Collimator mirror,
 + DCM,
 + refocusing mirror

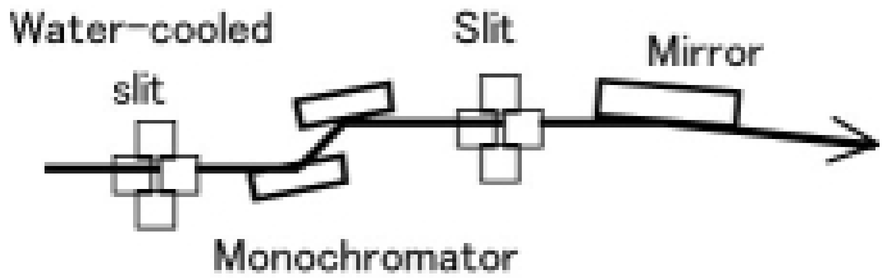


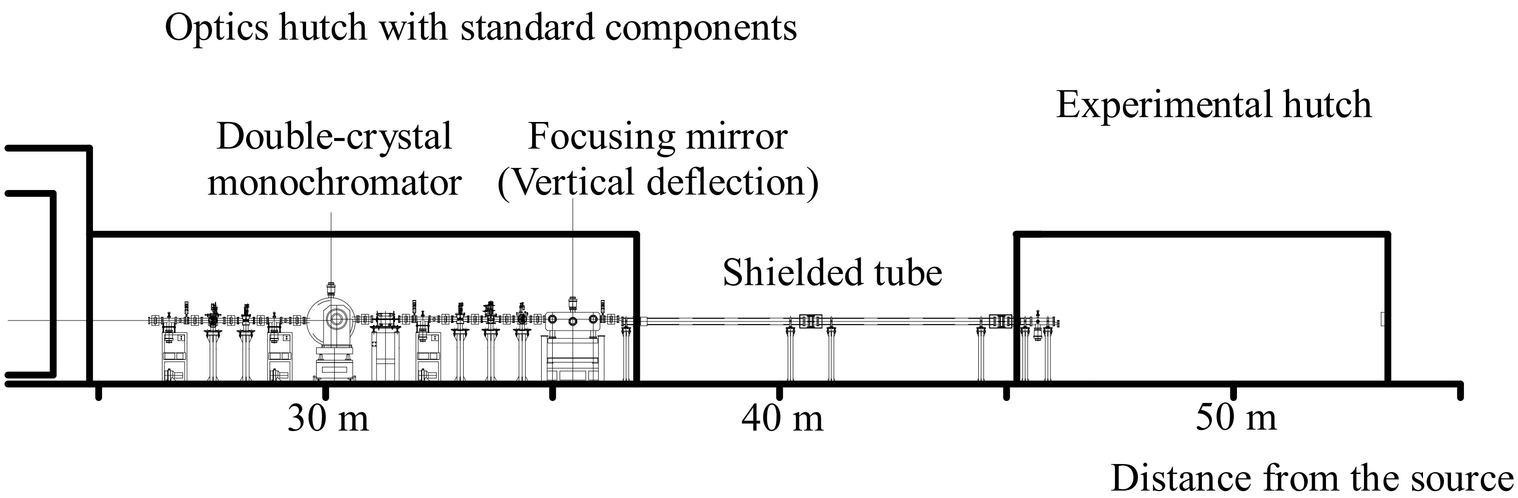
Optical layout for energy range less than 60 keV



Protein crystallography

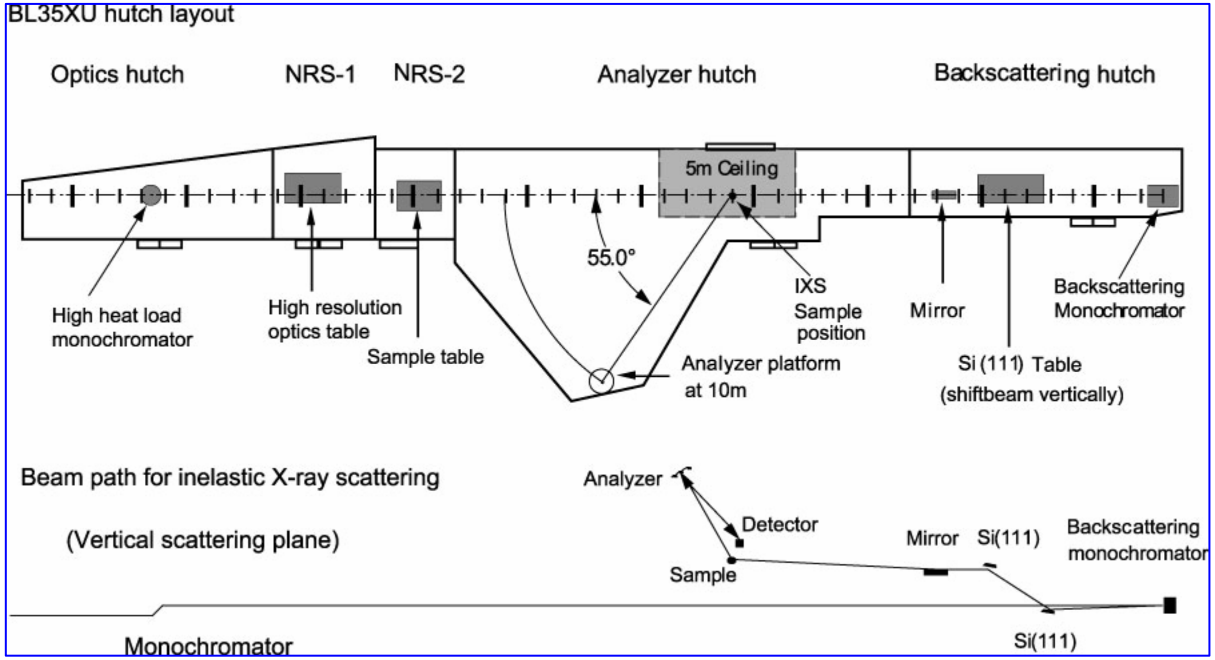
- Bending magnet
- DCM + focusing mirror

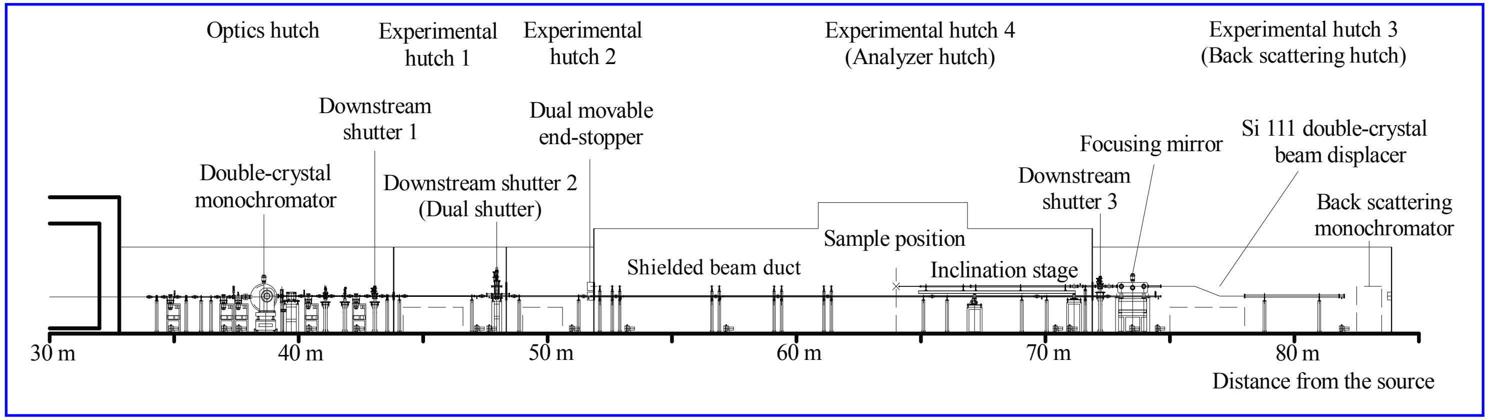




High resolution inelastic scattering

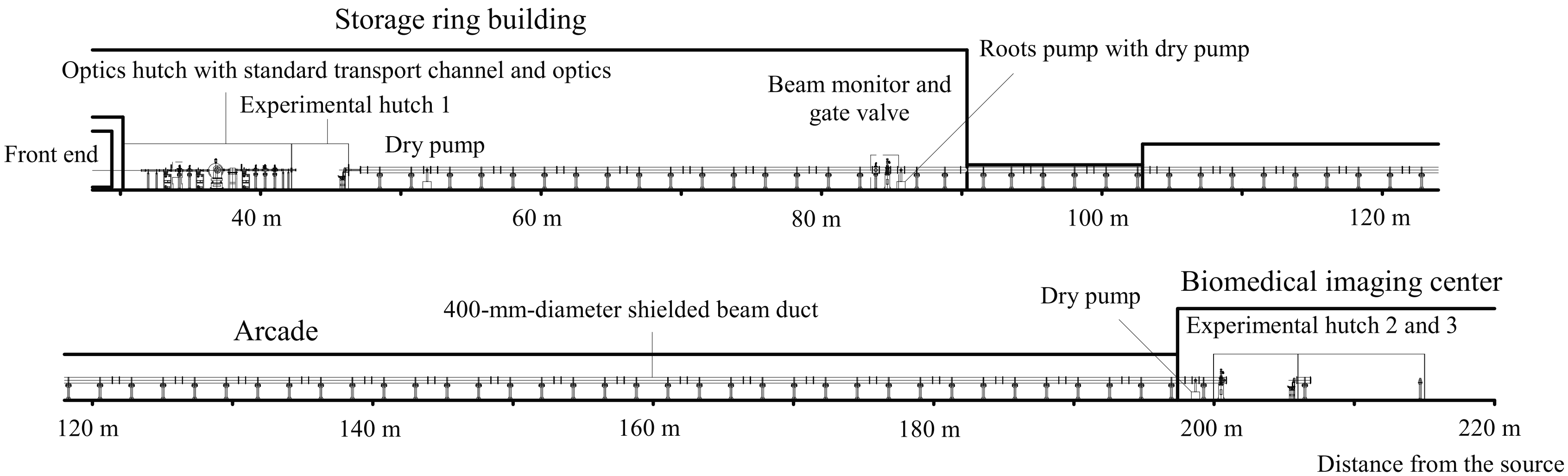
- Undulator
- DCM + back-reflection monochromator & analyzer (w/ ~meV resolution)

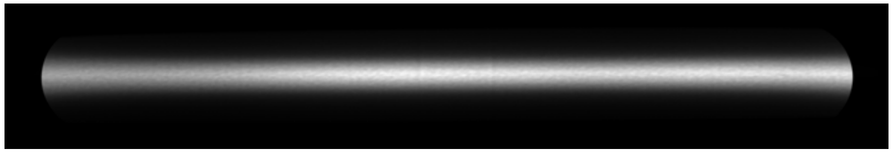




200-m-long beamline

- Bending magnet
- DCM

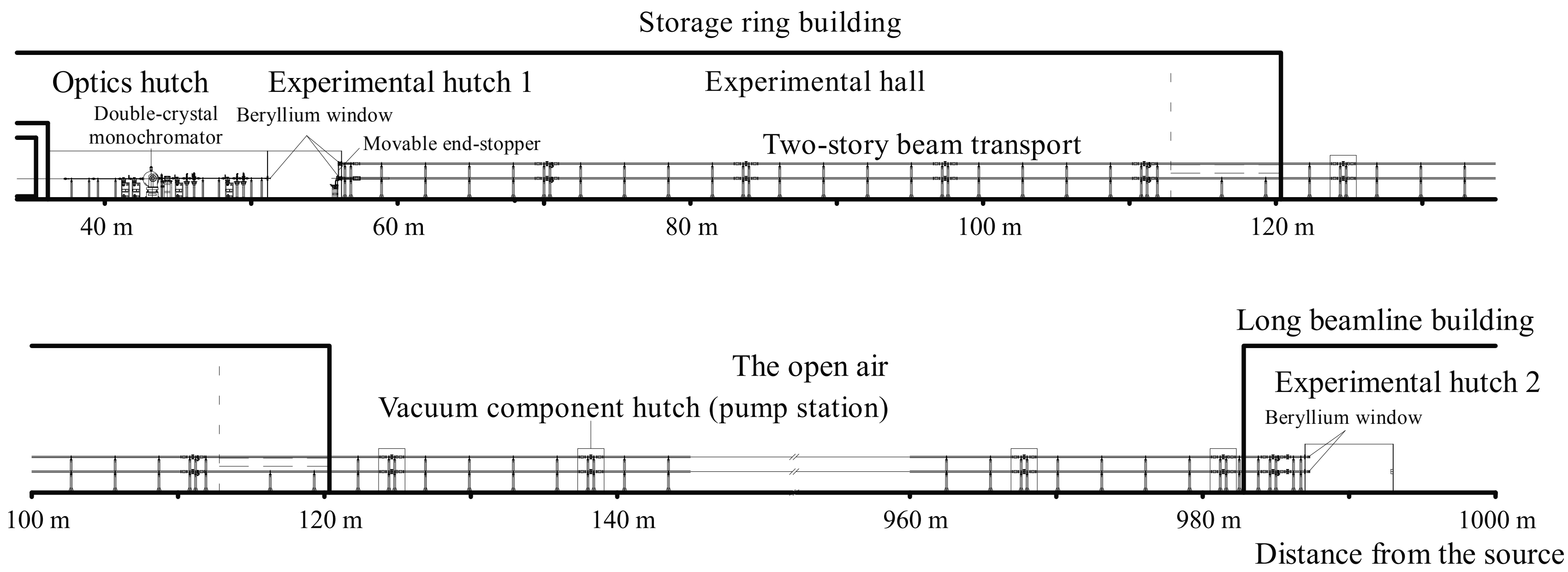




300-mm-wide beam at end-station

1-km-long beamline

- Undulator
- DCM + tandem mirror



Wide and spatially-coherent X-rays at 1-km end station

Summary

- Just only starting point of X-ray beamline design is shown here,

  w/ light source, monochromator, mirror,...

- It helps to figure out what we can obtain from the beamline.

- We will have to go into details of design refinement using;
  FEA (ANSYS), ray-tracing (SHADOW,...), shielding calculation,...

- Standardization of good components helps beamline design
  and saves the cost, man-power, and other resources.

- Ray-tracing → wave simulation for "diffraction limited source and optics"

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Thank you for your attention.